

TITLE OF THE INVENTION

Basic Compound, Resist Composition and Patterning Process

5

FIELD OF THE INVENTION

The present invention relates to a novel resist composition suitable for microfabrication technology, and more particularly to a chemical amplification resist composition. It also relates to a patterning process using the resist composition.

BACKGROUND ART

Of the efforts currently being made to achieve a finer pattern rule in the drive for higher integration and operating speeds in LSI devices, deep-ultraviolet lithography is thought to hold particular promise as the next generation in microfabrication technology. Deep-UV lithography is capable of fabrication to dimensions of 0.2 μm or less and, when a resist having low light absorption is used, can form patterns with sidewalls that are nearly perpendicular to the substrate. One technology that has attracted a good deal of attention recently utilizes high-intensity KrF and ArF excimer lasers as the deep-UV light source. This technology is being used in large-volume production, prompting a desire for resists having a low light absorption and a high sensitivity.

Acid-catalyzed, positive-working chemical amplification resists (e.g., JP-B 2-27660 and JP-A 63-27829) developed in response to the above needs are endowed with excellent properties, including a high sensitivity, high resolution and good dry-etching resistance, which make them especially promising as resists for deep-UV lithography.

However, one problem with chemical amplification resists is that, when the standing time from exposure to post exposure bake (PEB) is long, the line pattern formed during patterning acquires a "T-top" shape characterized by widening

at the top of the pattern. This defect is called "post exposure delay" (PED). Another problem with such resists is "footing," which is a widening of the resist pattern close to the substrate that occurs on a basic substrate, particularly  
5 a silicon nitride or titanium nitride substrate. The T-top effect is believed to result from a decrease in solubility at the surface of the resist film, and the footing effect at the substrate surface appears to arise from a decline in solubility near the substrate. An additional problem is that  
10 acid-labile group elimination is a dark reaction which proceeds during the interval between the exposure step and the PEB step, reducing the final dimensions of the pattern lines.

These problems represent major drawbacks to the  
15 practical use of chemical amplification resists. Because of such defects, prior-art positive-working chemical amplification resists are difficult to dimensionally control in the lithographic process, and dimensional control is also lost during dry etching of the substrate (see, for example, W.  
20 Hinsberg et al., *Journal of Photopolymer Science and Technology*, Vol. 6, No. 4, 535-546 (1993); and T. Kumada et al., *ibid.*, 571-574).

In positive-working chemical amplification resists,  
25 the problems of PED and footing on the substrate surface are believed to be caused in large part by basic compounds which are either airborne or present on the surface of the substrate. The acid at the surface of the resist film that has been generated by exposure reacts with airborne bases and is deactivated. Prolonged standing until post-exposure bake  
30 results in a corresponding increase in the amount of deactivated acid, making it more difficult for the acid-labile groups to decompose. A substantially insolubilized layer thus forms at the surface, giving the resist pattern a T-top shape.

35 It is well-known in the art that the addition of a basic compound can check the influence of airborne bases, and is thus effective also against PED (see, for example, JP-A

5-232706, JP-A 5-249683, JP-A 5-158239, JP-A 5-249662, JP-A  
5-257282, JP-A 5-289322, JP-A 5-289340, JP-A 6-194834, JP-A  
6-242605, JP-A 6-242606, JP-A 6-263716, JP-A 6-263717, JP-A  
6-266100, JP-A 6-266111, JP-A 7-128859, JP-A 7-92678, JP-A  
5 7-92680, JP-A 7-92681, JP-A 7-120929 and JP-A 7-134419).

Familiar basic compounds include nitrogenous compounds such as amine compounds and amide compounds. Specific examples include pyridine, polyvinylpyridine, aniline, N-methylaniline, N,N-dimethylaniline, o-toluidine, m-toluidine, p-toluidine, 2,4-lutidine, quinoline, isoquinoline, formamide, N-methylformamide, N,N-dimethylformamide, acetamide, N-methylacetamide, N,N-dimethylacetamide, 2-pyrrolidone, N-methylpyrrolidone, imidazole,  $\alpha$ -picoline,  $\beta$ -picoline,  $\gamma$ -picoline, 15 o-aminobenzoic acid, m-aminobenzoic acid, p-aminobenzoic acid, 1,2-phenylenediamine, 1,3-phenylenediamine, 1,4-phenylenediamine, 2-quinolinecarboxylic acid, 2-amino-4-nitrophenol, and triazine compounds such as 20 2-(p-chlorophenyl)-4,6-trichloromethyl-S-triazine.

Of these, pyrrolidone, N-methylpyrrolidone, o-aminobenzoic acid, m-aminobenzoic acid, p-aminobenzoic acid and 1,2-phenylenediamine are preferred.

These nitrogenous compounds are weak bases and can 25 alleviate the T-top problem, but such compounds are unable to control the reaction when highly reactive acid-labile groups are used; that is, they cannot control acid diffusion. With the addition of a weak base, the dark reactions in PED in particular proceed in unexposed areas, causing slimming of 30 the line dimensions and a loss of film thickness from the line surface during PED. To overcome such problems, it is desirable to add a strong base. However, a higher basicity is not necessarily better. For example, good effects cannot be obtained with the addition of the following super-strong 35 bases: DBU (1,8-diazabicyclo[5.4.0]-7-undecene), DBN (1,5-diazabicyclo[4.3.0]-5-nonene), 1,8-bis(dimethylamino)naphthalene or

quaternary ammonium hydroxides such as tetramethylammonium hydroxide.

The addition of a base having an excellent generated acid capturing effect works well to increase the contrast and thereby achieve a high resolution. The dissociation constants of the acid and base within water can be explained in terms of pKa, but the acid capturing ability within the resist film is not directly related to the pKa of the base. This is discussed by Hatakeyama et al. in *Journal of Photopolymer Science and Technology*, Vol. 13, No. 4, pp. 519-524 (2000).

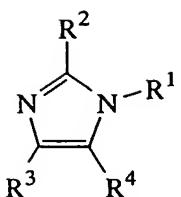
#### SUMMARY OF THE INVENTION

It is therefore an object of the invention to provide a resist composition which has a high resist film thickness loss preventing effect, and also has a high resolution and a good focus margin widening effect. Another object of the invention is to provide a patterning method which uses the resist composition. A further object of the invention is to provide a novel basic compound suited for use in the resist composition.

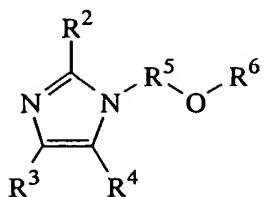
The inventor has found that basic compounds of general formula (1), especially general formulae (2) to (6) below which bear polar functional groups such as carbonyl, ester, ether, sulfide, carbonate, cyano or acetal and have an imidazole skeleton can be prepared easily and in a high yield by the methods described later. When added in an appropriate amount to a resist, these compounds are highly effective for preventing a loss of resist film thickness and endow the resist composition with a high resolution and a focus margin widening effect.

The present invention provides resist compositions, patterning processes, and basic compounds, defined below.

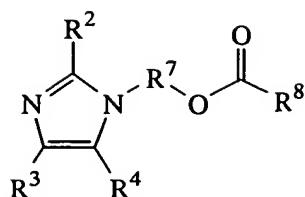
[I] A resist composition comprising one or more basic compounds represented by the general formulae (1) to (6).



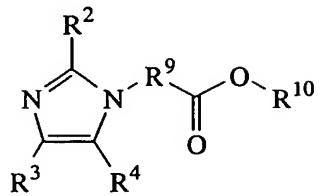
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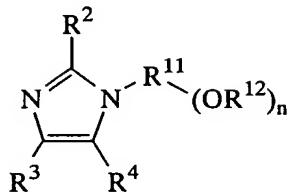
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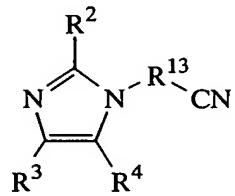
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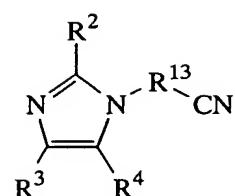
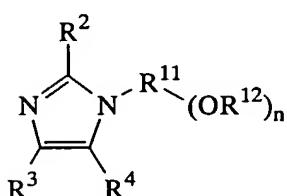
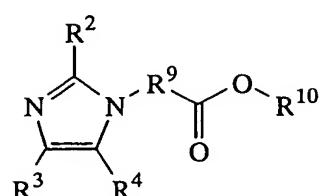
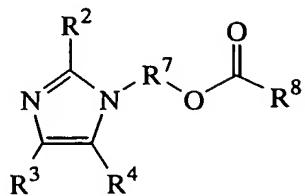
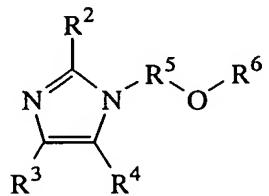


(6)

Herein R<sup>1</sup> is a straight, branched or cyclic alkyl group of 2 to 20 carbon atoms bearing at least one polar functional group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms; R<sup>5</sup>, R<sup>7</sup>, R<sup>9</sup> and R<sup>13</sup> are each independently a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; R<sup>6</sup> and R<sup>8</sup> are each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>10</sup> is an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>11</sup> is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms; R<sup>12</sup> is each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R<sup>12</sup> may bond together to form a ring; and n is equal to 2, 3, 4 or 5.

- [III] A positive-working resist composition comprising:
- (A) the basic compound of [I];
  - (B) an organic solvent;
  - (C) a base resin having an acid labile group-protected acidic functional group which is alkali-insoluble or substantially alkali-insoluble, but becomes alkali-soluble when the acid labile group is eliminated;
- 5 (D) a photoacid generator; and optionally,
- (E) a dissolution inhibitor.
- 10 [III] A negative-working resist composition comprising:
- (A) the basic compound of [I];
  - (B) an organic solvent;
  - (C') a base resin which is alkali-soluble, but becomes substantially alkali-insoluble when crosslinked with a
- 15 crosslinking agent (F);
- (D) a photoacid generator; and
  - (F) a crosslinking agent which induces crosslinkage under the action of an acid.
- [IV] A patterning process comprising the steps of:
- 20 (1) applying the resist composition of [II] or [III] onto a substrate;
- (2) heat treating the applied resist, then exposing the heat-treated resist through a photomask to high-energy radiation having a wavelength of at most 300 nm or an
- 25 electron beam; and
- (3) heat treating the exposed resist, then developing the resist with a liquid developer.

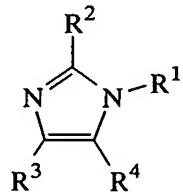
[V] Basic compounds represented by the general formulae (2) to (6).



Herein R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms; R<sup>5</sup>, R<sup>7</sup>, R<sup>9</sup> and R<sup>13</sup> are each independently a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; R<sup>6</sup> and R<sup>8</sup> are each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>10</sup> is an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>11</sup> is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms; R<sup>12</sup> is each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R<sup>12</sup> may bond together to form a ring; and n is equal to 2, 3, 4 or 5.

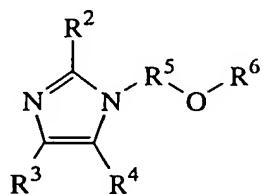
DETAILED DESCRIPTION OF THE INVENTION

The resist composition of the invention comprises one or more basic compounds having an imidazole skeleton and a polar functional group, represented by the general formula 5 (1).

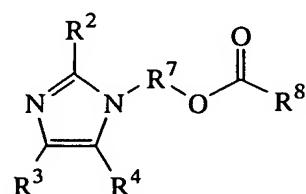


In formula (1), R¹ is a straight, branched or cyclic alkyl group of 2 to 20 carbon atoms bearing at least one polar functional group selected from among hydroxyl, carbonyl, 10 ester, ether, sulfide, carbonate, cyano and acetal groups; R², R³ and R⁴ are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms.

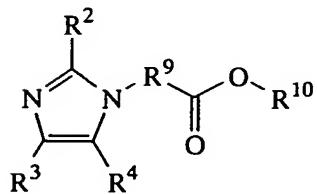
15 Of the basic compounds of formula (1), basic compounds of the general formulae (2) to (6) below are preferred. The preferred resist composition comprises one or more basic compounds represented by the general formulae (2) to (6). It is noted that basic compounds of formulae (2) to (6) are 20 novel.



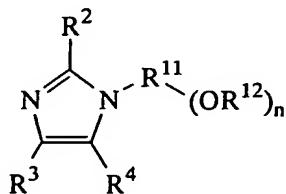
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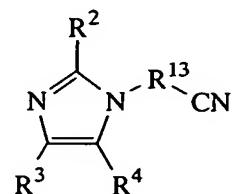
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(5)



(6)

Herein R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms; R<sup>5</sup>, R<sup>7</sup>, R<sup>9</sup> and R<sup>13</sup> are each  
5 independently a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; R<sup>6</sup> and R<sup>8</sup> are each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups;  
10 R<sup>10</sup> is an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>11</sup> is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms; R<sup>12</sup> is each  
15 independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R<sup>12</sup> may bond together to form a ring; and n is equal to 2, 3, 4 or 5.

In formula (1), R<sup>1</sup> represents a straight, branched or cyclic alkyl group of 2 to 20 carbon atoms, and preferably 2 to 10 carbon atoms, having at least one polar functional group selected from among hydroxyl, carbonyl, ether, ester, carbonate, sulfide, cyano and acetal groups. Specific, non-limiting examples of the polar functional group-bearing alkyl groups include 2-oxotetrahydrofuran-3-yl, 5-oxotetrahydrofuran-3-yl, 2-oxotetrahydro-2H-pyran-3-yl, 2-tetrahydrofuryl, tetrahydro-2H-pyran-2-yl, tetrahydro-2H-pyran-4-yl, tetrahydrofurfuryl,  
25 2-tetrahydrothienyl, 2-tetrahydronenyl, 3,3-dicyanopropyl, and 3,3-bis(methoxycarbonyl)propyl groups as well as groups having some of R<sup>5</sup>, R<sup>6</sup>, R<sup>7</sup>, R<sup>8</sup>, R<sup>9</sup>, R<sup>10</sup>, R<sup>11</sup>, R<sup>12</sup> and R<sup>13</sup> such as -R<sup>5</sup>-O-R<sup>6</sup>, -R<sup>7</sup>-OCO-R<sup>8</sup>, R<sup>9</sup>-COO-R<sup>10</sup>, -R<sup>11</sup>-(OR<sup>12</sup>)<sub>n</sub> and -R<sup>13</sup>-CN.

In formulae (1) to (6), R<sup>2</sup>, R<sup>3</sup>, and R<sup>4</sup> represent hydrogen, straight, branched or cyclic alkyl groups having 1 to 10 carbon atoms, aryl groups having 6 to 10 carbon atoms or aralkyl groups having 7 to 10 carbon atoms, examples of

which include, but are not limited to, hydrogen, methyl, ethyl, propyl, isopropyl, butyl, isobutyl, pentyl, hexyl, decyl, cyclopentyl, cyclohexyl, phenyl, tolyl, xylyl, naphthyl, benzyl and phenethyl.

5 In formulae (2), (3), (4) and (6), R<sup>5</sup>, R<sup>7</sup>, R<sup>9</sup> and R<sup>13</sup> represent straight, branched or cyclic alkylene groups of 1 to 10 carbon atoms, examples of which include, but are not limited to, methylene, ethylene, ethyldene, propylene, isopropylidene, 1,3-propanediyl, 1,4-butanediyl,  
10 1,2-butanediyl, 1,5-pantanediyl, 1,2-pantanediyl, 1,10-decanediyl, 1,2-cyclopantanediyl, 1,2-cyclohexanediyl, and 1,4-cyclohexanediyl.

In formulae (2) and (3), R<sup>6</sup> and R<sup>8</sup> represent hydrogen atoms or alkyl groups of 1 to 15 carbon atoms which may  
15 contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups. Illustrative, non-limiting examples include hydrogen, methyl, ethyl, propyl, isopropyl, butyl, isobutyl, pentyl, hexyl, decyl, pentadecyl, cyclopentyl, cyclohexyl,  
20 2-tetrahydrofuryl, 2-oxo-3-tetrahydrofuryl, 2-tetrahydro-2H-pyranyl, tetrahydrofurfuryl, methoxymethyl, ethoxymethyl, propoxymethyl, (2-methoxyethoxy)methyl, cyanomethyl, methylthiomethyl, acetoxyethyl, formyloxyethyl, 1,3-dioxolan-4-ylmethyl,  
25 (2,2-dimethyl-1,3-dioxolan-4-yl)methyl, (2-oxo-1,3-dioxolan-4-yl)methyl, methoxycarbonyl, ethoxycarbonyl, t-butoxycarbonyl, 2-hydroxyethyl, 1-methoxyethyl, 2-methoxyethyl, 1-ethoxyethyl, 2-ethoxyethyl, 2-propoxyethyl, 2-(2-methoxyethoxy)ethyl,  
30 2-(2-tetrahydro-2H-pyranyloxy)ethyl, 2-formyloxyethyl, 2-acetoxyethyl, 2-propionyloxyethyl, 2-butyryloxyethyl, 2-valeryloxyethyl, 2-hexanoyloxyethyl, 2-cyanoethyl, 2-methylthioethyl, 2-methoxycarbonyloxyethyl, 2,2-dimethoxyethyl, 2,2-diethoxyethyl, 3,3-dimethoxypropyl,  
35 3,3-diethoxypropyl, 2-hydroxypropyl, 2-methoxypropyl, 2-acetoxypropyl, 2-propionyloxypropyl, 3-hydroxypropyl and 4-hydroxybutyl.

In formula (4), R<sup>10</sup> represents alkyl groups of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups. Illustrative, 5 non-limiting examples include methyl, ethyl, propyl, isopropyl, butyl, isobutyl, pentyl, hexyl, decyl, pentadecyl, cyclopentyl, cyclohexyl, 2-tetrahydrofuryl, 2-oxo-3-tetrahydrofuryl, 2-tetrahydro-2H-pyranyl, tetrahydrofurfuryl, methoxymethyl, ethoxymethyl, 10 propoxymethyl, (2-methoxyethoxy)methyl, cyanomethyl, methylthiomethyl, 1,3-dioxolan-4-ylmethyl, (2,2-dimethyl-1,3-dioxolan-4-yl)methyl, (2-oxo-1,3-dioxolan-4-yl)methyl, 2-hydroxyethyl, 1-methoxyethyl, 2-methoxyethyl, 1-ethoxyethyl, 2-ethoxyethyl, 15 2-propoxyethyl, 2-(2-methoxyethoxy)ethyl, 2-(2-tetrahydro-2H-pyranloxy)ethyl, 2-formyloxyethyl, 2-acetoxyethyl, 2-propionyloxyethyl, 2-butyryloxyethyl, 2-valeryloxyethyl, 2-hexanoyloxyethyl, 2-cyanoethyl, 2-methylthioethyl, 2-methoxycarbonyloxyethyl, 20 2,2-dimethoxyethyl, 2,2-diethoxyethyl, 3,3-dimethoxypropyl, 3,3-diethoxypropyl, 2-hydroxypropyl, 2-methoxypropyl, 2-acetoxypropyl, 2-propionyloxypropyl, 3-hydroxypropyl and 4-hydroxybutyl.

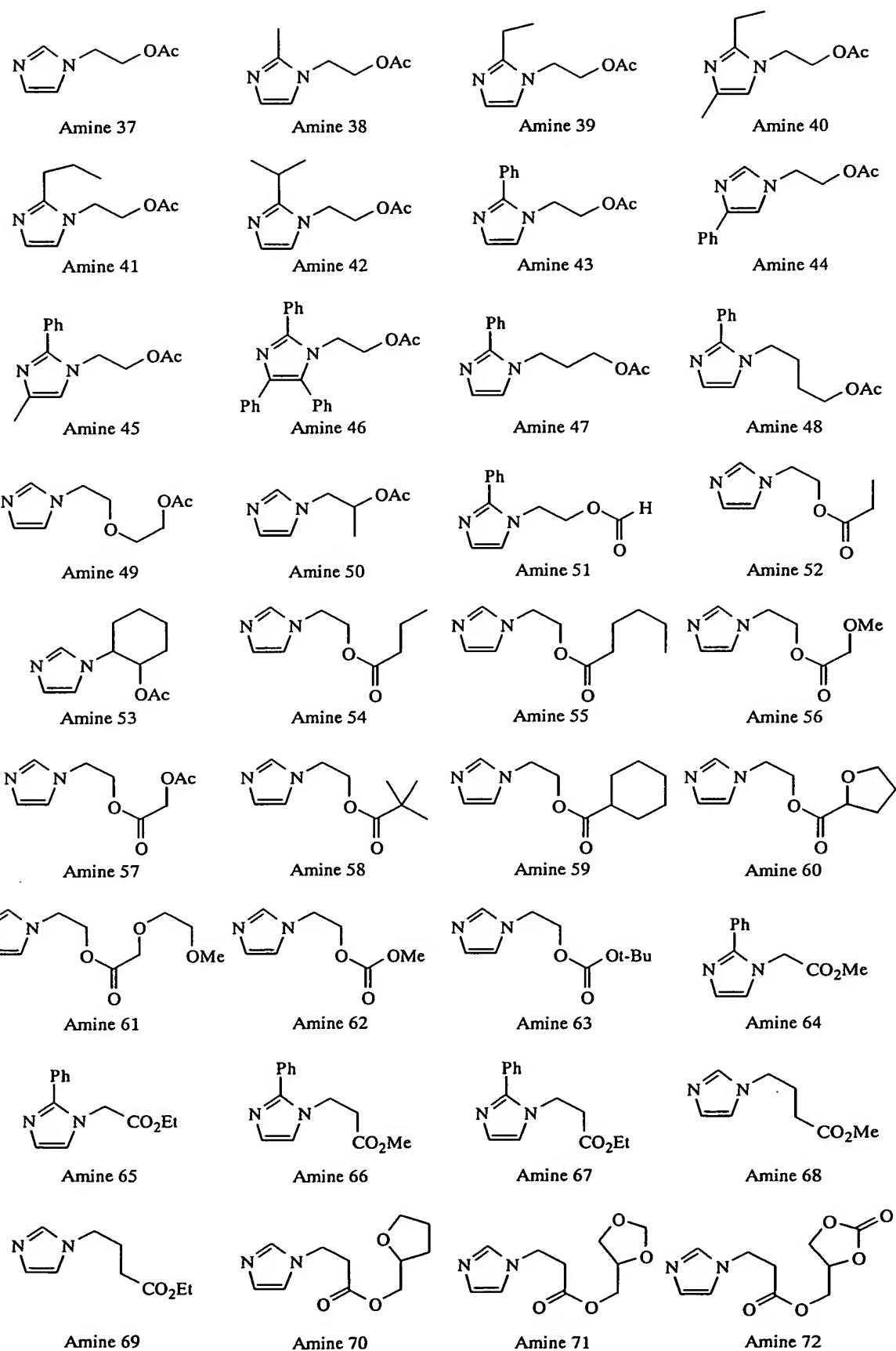
In formula (5), R<sup>11</sup> represents (n+1)-valent, straight, 25 branched or cyclic hydrocarbon groups of 2 to 10 carbon atoms, wherein n = 2, 3, 4 or 5. Illustrative examples include, but are not limited to, 1,1,2-ethanetriyl, 1,2,3-propanetriyl, 1,1,3-propanetriyl, 1,1,2,3-propanetetrayl, 1,1,3-cyclohexanetriyl, and 1,2,3,4,5,6-cyclohexanehexayl 30 groups.

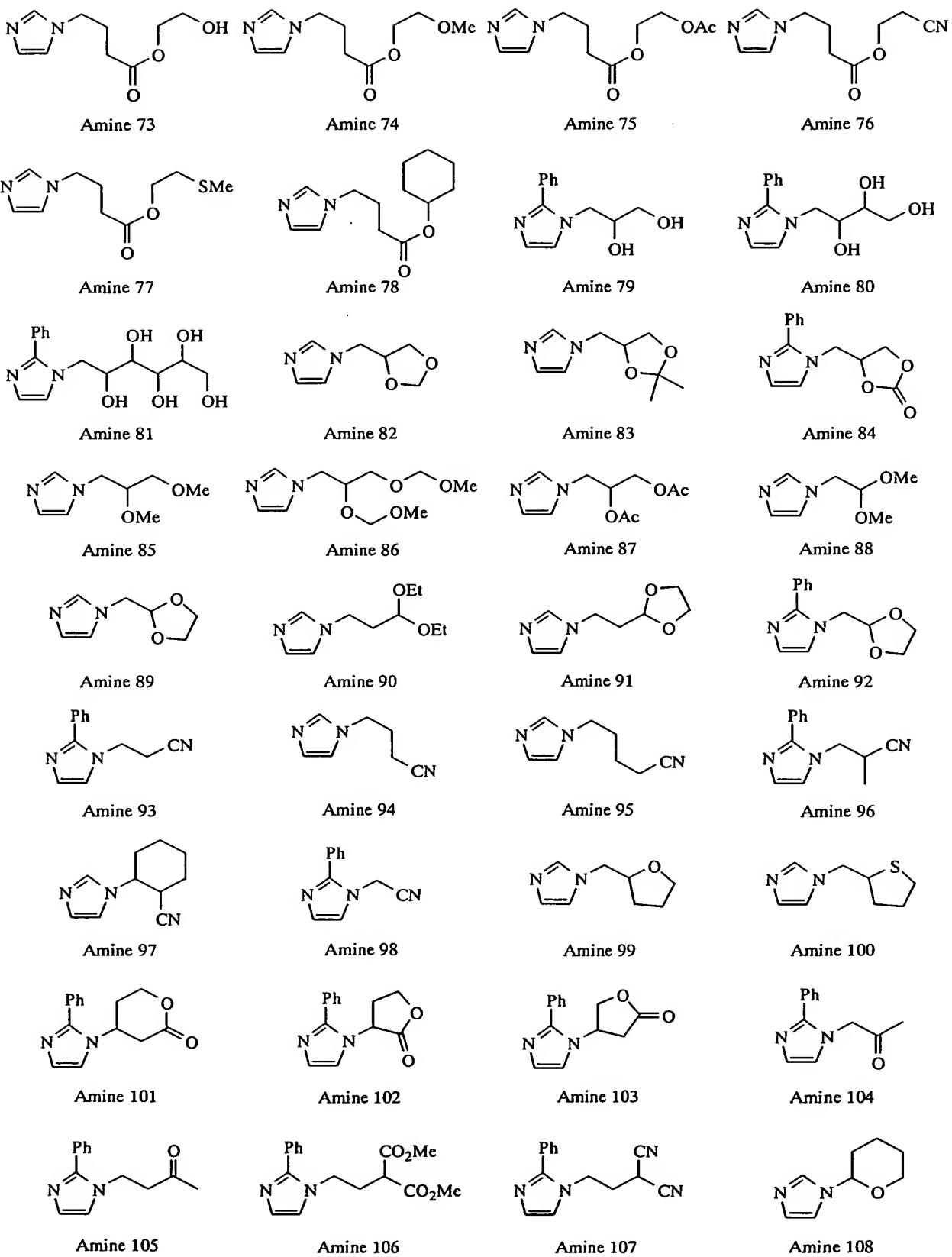
In formula (5), R<sup>12</sup> which may be the same or different represents hydrogen atoms or alkyl groups of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, 35 cyano and acetal groups. Illustrative examples include, but are not limited to, hydrogen, methyl, ethyl, propyl, isopropyl, butyl, isobutyl, pentyl, hexyl, decyl, pentadecyl,

cyclopentyl, cyclohexyl, 2-tetrahydrofuryl,  
2-oxo-3-tetrahydrofuryl, 2-tetrahydro-2H-pyranyl,  
tetrahydrofurfuryl, methoxymethyl, ethoxymethyl,  
propoxymethyl, (2-methoxyethoxy)methyl, cyanomethyl,  
5 methylthiomethyl, acetoxyethyl, formyloxymethyl,  
1,3-dioxolan-4-ylmethyl,  
(2,2-dimethyl-1,3-dioxolan-4-yl)methyl,  
(2-oxo-1,3-dioxolan-4-yl)methyl, methoxycarbonyl,  
ethoxycarbonyl, t-butoxycarbonyl, 2-hydroxyethyl,  
10 1-methoxyethyl, 2-methoxyethyl, 1-ethoxyethyl, 2-ethoxyethyl,  
2-propoxyethyl, 2-(2-methoxyethoxy)ethyl,  
2-(2-tetrahydro-2H-pyranyloxy)ethyl, 2-formyloxethyl,  
2-acetoxyethyl, 2-propionyloxethyl, 2-butyryloxethyl,  
2-valeryloxethyl, 2-hexanoyloxethyl, 2-cyanoethyl,  
15 2-methylthioethyl, 2-methoxycarbonyloxyethyl, 2-hydroxypropyl,  
2-methoxypropyl, 2-acetoxypropyl, 2-propionyloxypropyl,  
3-hydroxypropyl, and 4-hydroxybutyl. Alternatively, two of  
R<sup>12</sup> may bond together to form a ring, examples of which  
include 1,3-dioxolane, 2,2-dimethyl-1,3-dioxolane,  
20 2-methyl-1,3-dioxolane, 2-oxo-1,3-dioxolane, 1,3-dioxane,  
2,2-dimethyl-1,3-dioxane, and 2-oxo-1,3-dioxane, but are not  
limited thereto.

Specific examples of the basic compounds having an  
imidazole skeleton and a polar functional group moiety  
25 according to the invention include, but are not limited to,  
the following. In the structural formulas that appear below,  
"Me" represents methyl, "Et" represents ethyl, "t-Bu"  
represents t-butyl, "Ac" represents acetyl and "Ph"  
represents phenyl.







According to the invention, the basic compounds have an imidazole skeleton and a polar functional group moiety within the molecule. The polar functional group having a high kinetic affinity to acids can be placed at a suitable position near the amine nitrogen in imidazole. As a result, generated acids can be rapidly captured, enabling photoresists containing these basic compounds to achieve a high resolution and a wide focus margin. By selecting an optimal combination from among the possible combinations of R<sup>1</sup> to R<sup>4</sup> in formula (1), the basicity, acid capturing rate and diffusion rate within the resist can be suitably adjusted. Therefore, the basic compound additives are compatible with a broad range of resist polymers and photoacid generators.

The inventive resist composition is most preferably either a positive-working chemical amplification resist composition which includes:

- (A) the above-described basic compound,
- (B) an organic solvent,
- (C) a base resin having an acid labile group-protected acidic functional group, which is alkali-insoluble or substantially alkali-insoluble, but becomes alkali-soluble when the acid labile group is eliminated,
- (D) a photoacid generator and optionally,
- (E) a dissolution inhibitor;

or a negative-working chemical amplification resist composition which includes:

- (A) the above-described basic compound,
- (B) an organic solvent,
- (C') a base resin which is alkali-soluble, but becomes substantially alkali-insoluble when crosslinked with a crosslinking agent (F),
- (D) a photoacid generator, and
- (F) a crosslinking agent which induces crosslinkage under the action of an acid.

These components are described in detail.

(B) Organic solvent

The organic solvent used herein may be any organic solvent in which the base resin, photoacid generator, and other components are soluble. Illustrative, non-limiting, examples of the organic solvent include ketones such as cyclohexanone and methyl-2-n-amylketone; alcohols such as 3-methoxybutanol, 3-methyl-3-methoxybutanol, 1-methoxy-2-propanol, and 1-ethoxy-2-propanol; ethers such as propylene glycol monomethyl ether, ethylene glycol monomethyl ether, propylene glycol monoethyl ether, ethylene glycol dimethyl ether, and diethylene glycol dimethyl ether; esters such as propylene glycol monomethyl ether acetate, propylene glycol monoethyl ether acetate, ethyl lactate, ethyl pyruvate, butyl acetate, methyl 3-methoxypropionate, ethyl 3-ethoxypropionate, tert-butyl acetate, tert-butyl propionate, and propylene glycol mono-tert-butyl ether acetate; and lactones such as  $\gamma$ -butyrolactone. These solvents may be used alone or in combinations of two or more thereof. Of the above organic solvents, it is recommended to use diethylene glycol dimethyl ether, 1-ethoxy-2-propanol, propylene glycol monomethyl ether acetate, cyclohexanone and mixtures thereof because the photoacid generator is most soluble therein.

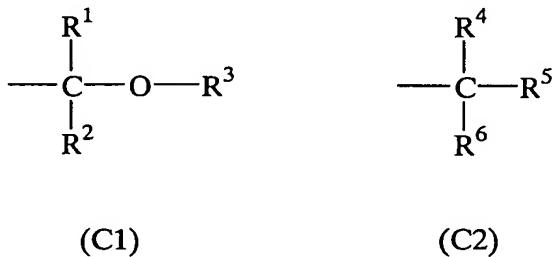
An appropriate amount of the organic solvent used is about 200 to 3,000 parts, especially about 400 to 2,000 parts by weight per 100 parts by weight of the base resin.

30 (C) Base polymer

The base polymers used as component (C) or (C') in the inventive compositions include polyhydroxystyrene (PHS), and copolymers of PHS with styrene, (meth)acrylic acid esters or other polymerizable olefinic compounds, for KrF excimer laser resist use; (meth)acrylic acid ester polymers, alternating copolymers of cycloolefin with maleic anhydride, copolymers containing vinyl ethers or (meth)acrylic acid esters,

polynorbornene, and ring-opening metathesis polymerized cycloolefins, for ArF excimer laser resist use; and fluorinated forms of the foregoing polymers (for both KrF and ArF laser uses) for F<sub>2</sub> excimer laser resist use, although the base polymers are not limited thereto. The base polymers may be used alone or in admixture of two or more. In the case of positive resist compositions, it is a common practice to substitute acid labile groups for hydroxyl groups on phenol, carboxyl groups or fluorinated alkyl alcohols for reducing the rate of dissolution in unexposed regions.

The acid labile groups to be introduced into the base polymers may be selected from a variety of such groups, preferably from acetal groups of 2 to 30 carbon atoms and tertiary alkyl groups of 4 to 30 carbon atoms having the formulae (C1) and (C2), respectively.



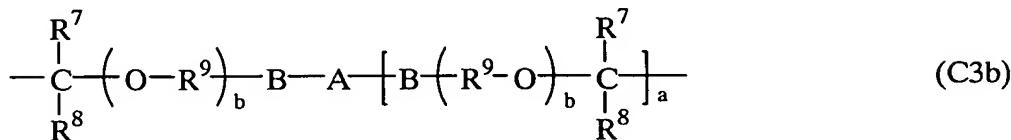
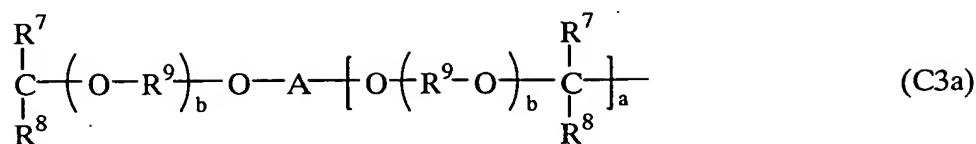
In formulae (C1) and (C2), R<sup>1</sup> and R<sup>2</sup> each are hydrogen or a straight, branched or cyclic C<sub>1</sub>-C<sub>20</sub> alkyl group, which may contain a hetero atom such as oxygen, sulfur, nitrogen or fluorine, R<sup>3</sup>, R<sup>4</sup>, R<sup>5</sup> and R<sup>6</sup> each are a straight, branched or cyclic C<sub>1</sub>-C<sub>20</sub> alkyl group, a C<sub>6</sub>-C<sub>10</sub> aryl group or a C<sub>1</sub>-C<sub>10</sub> aralkyl group, which may contain a hetero atom such as oxygen, sulfur, nitrogen or fluorine. A pair of R<sup>1</sup> and R<sup>2</sup>, a pair of R<sup>1</sup> and R<sup>3</sup>, a pair of R<sup>2</sup> and R<sup>3</sup>, a pair of R<sup>4</sup> and R<sup>5</sup>, a pair of R<sup>4</sup> and R<sup>6</sup>, or a pair of R<sup>5</sup> and R<sup>6</sup>, taken together, may form a ring with the carbon atom to which they are attached.

Illustrative examples of the acetal group of formula (C1) include, but are not limited to, methoxymethyl, ethoxymethyl, propoxymethyl, butoxymethyl, isopropoxymethyl, t-butoxymethyl, 1-methoxyethyl, 1-methoxypropyl, 1-methoxybutyl, 1-ethoxyethyl, 1-ethoxypropyl, 1-ethoxybutyl,

1-propoxyethyl, 1-propoxypropyl, 1-propoxybutyl,  
1-cyclopentyloxyethyl, 1-cyclohexyloxyethyl,  
2-methoxyisopropyl, 2-ethoxyisopropyl, 1-phenoxyethyl,  
1-benzyloxyethyl, 1-phenoxypropyl, 1-benzyloxypropyl,  
5 1-adamantyloxyethyl, 1-adamantyloxypropyl, 2-tetrahydrofuryl,  
2-tetrahydro-2H-pyranyl,  
1-(2-cyclohexanecarbonyloxyethoxy)ethyl,  
1-(2-cyclohexanecarbonyloxyethoxy)propyl,  
1-[2-(1-adamantylcarbonyloxy)ethoxy]ethyl, and  
10 1-[2-(1-adamantylcarbonyloxy)ethoxy]propyl.

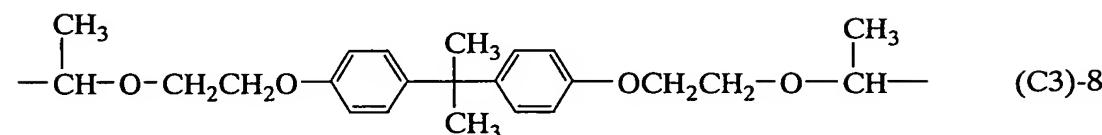
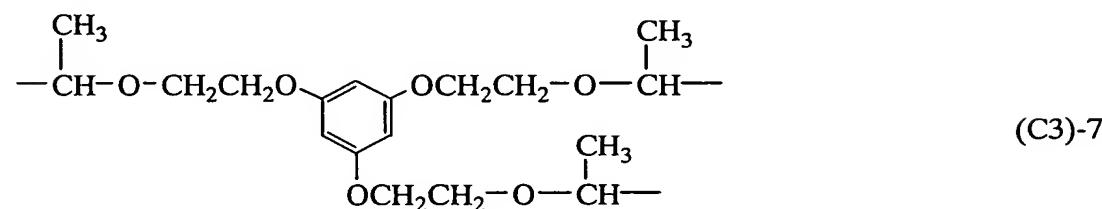
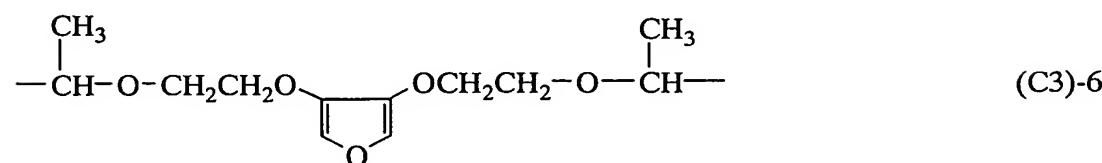
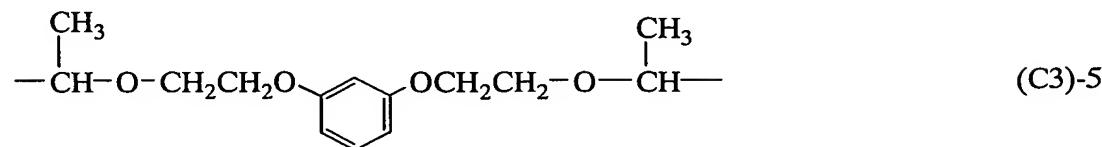
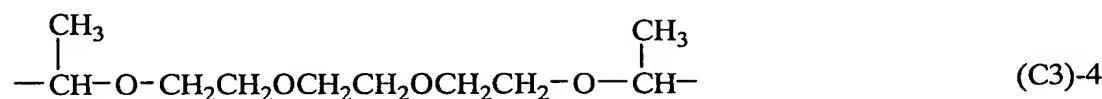
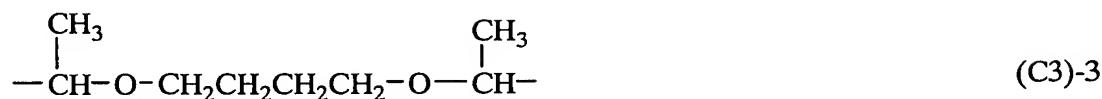
Illustrative examples of the tertiary alkyl group of formula (C2) include, but are not limited to, t-butyl, t-pentyl, 1-ethyl-1-methylpropyl, 1,1-diethylpropyl, 1,1,2-trimethylpropyl, 1-adamantyl-1-methylethyl,  
15 1-methyl-1-(2-norbornyl)ethyl,  
1-methyl-1-(tetrahydrofuran-2-yl)ethyl,  
1-methyl-1-(7-oxanorbornan-2-yl)ethyl, 1-methylcyclopentyl,  
1-ethylcyclopentyl, 1-propylcyclopentyl,  
1-cyclopentylcyclopentyl, 1-cyclohexylcyclopentyl,  
20 1-(2-tetrahydrofuryl)cyclopentyl,  
1-(7-oxanorbornan-2-yl)cyclopentyl, 1-methylcyclohexyl,  
1-ethylcyclohexyl, 1-cyclopentylcyclohexyl,  
1-cyclohexylcyclohexyl, 2-methyl-2-norbornyl,  
2-ethyl-2-norbornyl, 8-methyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decyl,  
25 8-ethyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decyl,  
3-methyl-3-tetracyclo[4.4.0.1<sup>2,5</sup>.1<sup>7,10</sup>]dodecyl,  
3-ethyl-3-tetracyclo[4.4.0.1<sup>2,5</sup>.1<sup>7,10</sup>]dodecyl,  
2-methyl-2-adamantyl, 2-ethyl-2-adamantyl,  
1-methyl-3-oxo-1-cyclohexyl,  
30 1-methyl-1-(tetrahydrofuran-2-yl)ethyl,  
5-hydroxy-2-methyl-2-adamantyl, and  
5-hydroxy-2-ethyl-2-adamantyl.

In the base resin, at least 1 mol% of hydrogen atoms of hydroxyl groups may be substituted with acid labile groups  
35 of the following general formula (C3a) or (C3b) for crosslinkage between molecules or within a molecule.



Herein,  $R^7$  and  $R^8$  each are hydrogen or a straight, branched or cyclic alkyl group of 1 to 8 carbon atoms, or  $R^7$  and  $R^8$ , taken together, may form a ring, with the proviso  
5 that each of  $R^7$  and  $R^8$  is a straight or branched alkylene group of 1 to 8 carbon atoms when they form a ring.  $R^9$  is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms. Letter "a" is an integer of 1 to 7 and "b" is 0 or an integer of 1 to 10. "A" is a  $(a+1)$ -valent aliphatic or  
10 alicyclic saturated hydrocarbon group, aromatic hydrocarbon group or heterocyclic group of 1 to 50 carbon atoms, which may have an intervening hetero atom and in which the hydrogen atom attached to a carbon atom may be partially replaced by a hydroxyl group, carboxyl group, carbonyl group or fluorine  
15 atom. B is  $-CO-O-$ ,  $-NHCO-O-$  or  $-NHCONH-$ .

Illustrative examples of the crosslinking acetal linkages represented by formulae (C3a) and (C3b) are given below as (C3)-1 through (C3)-8, but not limited thereto.



Preferably the base polymer has a weight average molecular weight of 2,000 to 100,000. With Mw below 2,000, film formation and resolution may become poor. With Mw beyond 100,000, resolution may become poor or foreign matter may generate during pattern formation.

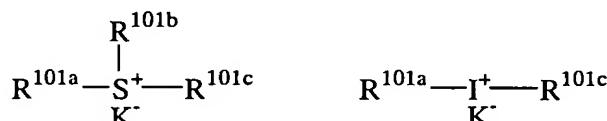
(D) Photoacid generator

The photoacid generator is a compound capable of generating an acid upon exposure to high energy radiation or electron beams and includes the following:

- 5        (i) onium salts of the formula (Pla-1), (Pla-2) or (Plb),  
          (ii) diazomethane derivatives of the formula (P2),  
          (iii) glyoxime derivatives of the formula (P3),  
          (iv) bisulfone derivatives of the formula (P4),  
          (v) sulfonic acid esters of N-hydroxyimide compounds of the  
10      formula (P5),  
          (vi)  $\beta$ -ketosulfonic acid derivatives,  
          (vii) disulfone derivatives,  
          (viii) nitrobenzylsulfonate derivatives,  
          (ix) sulfonate derivatives, and  
15      (x) oxime sulfonates.

These photoacid generators are described in detail.

- (i) Onium salts of formula (Pla-1), (Pla-2) or (Plb):



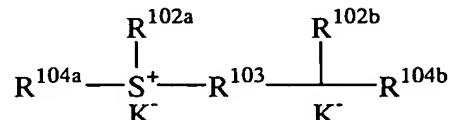
(Pla-1)

(Pla-2)

Herein,  $\text{R}^{101\text{a}}$ ,  $\text{R}^{101\text{b}}$ , and  $\text{R}^{101\text{c}}$  independently represent  
20 straight, branched or cyclic alkyl, alkenyl or oxoalkyl  
groups of 1 to 12 carbon atoms, aryl groups of 6 to 20 carbon  
atoms, or aralkyl or aryloxoalkyl groups of 7 to 12 carbon  
atoms, wherein some or all of the hydrogen atoms may be  
replaced by alkoxy or other groups. Also,  $\text{R}^{101\text{b}}$  and  $\text{R}^{101\text{c}}$ ,  
25 taken together, may form a ring.  $\text{R}^{101\text{b}}$  and  $\text{R}^{101\text{c}}$  each are  
alkylene groups of 1 to 6 carbon atoms when they form a ring.  
 $\text{K}^-$  is a non-nucleophilic counter ion.

$\text{R}^{101\text{a}}$ ,  $\text{R}^{101\text{b}}$ , and  $\text{R}^{101\text{c}}$  may be the same or different and  
are illustrated below. Exemplary alkyl groups include methyl,  
30 ethyl, propyl, isopropyl, n-butyl, sec-butyl, tert-butyl,  
pentyl, hexyl, heptyl, octyl, cyclopentyl, cyclohexyl,  
cycloheptyl, cyclopropylmethyl, 4-methylcyclohexyl,

cyclohexylmethyl, norbornyl, and adamantyl. Exemplary alkenyl groups include vinyl, allyl, propenyl, butenyl, hexenyl, and cyclohexenyl. Exemplary oxoalkyl groups include 2-oxocyclopentyl and 2-oxocyclohexyl as well as 2-oxopropyl, 5 2-cyclopentyl-2-oxoethyl, 2-cyclohexyl-2-oxoethyl, and 2-(4-methylcyclohexyl)-2-oxoethyl. Exemplary aryl groups include phenyl and naphthyl; alkoxyphenyl groups such as p-methoxyphenyl, m-methoxyphenyl, o-methoxyphenyl, ethoxyphenyl, p-tert-butoxyphenyl, and m-tert-butoxyphenyl; 10 alkylphenyl groups such as 2-methylphenyl, 3-methylphenyl, 4-methylphenyl, ethylphenyl, 4-tert-butylphenyl, 4-butylphenyl, and dimethylphenyl; alkynaphthyl groups such as methylnaphthyl and ethylnaphthyl; alkoxynaphthyl groups such as methoxynaphthyl and ethoxynaphthyl; dialkynaphthyl 15 groups such as dimethylnaphthyl and diethylnaphthyl; and dialkoxyphenyl groups such as dimethoxynaphthyl and diethoxynaphthyl. Exemplary aralkyl groups include benzyl, phenylethyl, and phenethyl. Exemplary aryloxalkyl groups are 2-aryl-2-oxoethyl groups such as 2-phenyl-2-oxoethyl, 20 2-(1-naphthyl)-2-oxoethyl, and 2-(2-naphthyl)-2-oxoethyl. Examples of the non-nucleophilic counter ion represented by K<sup>-</sup> include halide ions such as chloride and bromide ions, fluoroalkylsulfonate ions such as triflate, 1,1,1-trifluoroethanesulfonate, and nonafluorobutanesulfonate, 25 arylsulfonate ions such as tosylate, benzenesulfonate, 4-fluorobenzenesulfonate, and 1,2,3,4,5-pentafluorobenzenesulfonate, and alkylsulfonate ions such as mesylate and butanesulfonate.



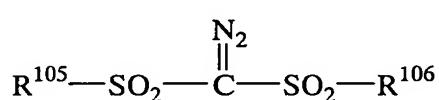
(P1b)

30 Herein, R<sup>102a</sup> and R<sup>102b</sup> independently represent straight, branched or cyclic alkyl groups of 1 to 8 carbon atoms. R<sup>103</sup> represents a straight, branched or cyclic alkylene groups of

1 to 10 carbon atoms.  $R^{104a}$  and  $R^{104b}$  independently represent 2-oxoalkyl groups of 3 to 7 carbon atoms.  $K^-$  is a non-nucleophilic counter ion.

Illustrative of the groups represented by  $R^{102a}$  and  $R^{102b}$  are methyl, ethyl, propyl, isopropyl, n-butyl, sec-butyl, tert-butyl, pentyl, hexyl, heptyl, octyl, cyclopentyl, cyclohexyl, cyclopropylmethyl, 4-methylcyclohexyl, and cyclohexylmethyl. Illustrative of the groups represented by  $R^{103}$  are methylene, ethylene, propylene, butylene, pentylene, hexylene, heptylene, octylene, nonylene, 1,4-cyclohexylene, 1,2-cyclohexylene, 1,3-cyclopentylene, 1,4-cyclooctylene, and 1,4-cyclohexanedimethylene. Illustrative of the groups represented by  $R^{104a}$  and  $R^{104b}$  are 2-oxopropyl, 2-oxocyclopentyl, 2-oxocyclohexyl, and 2-oxocycloheptyl. Illustrative examples of the counter ion represented by  $K^-$  are the same as exemplified for formulae (Pla-1) and (Pla-2).

(ii) Diazomethane derivatives of formula (P2)



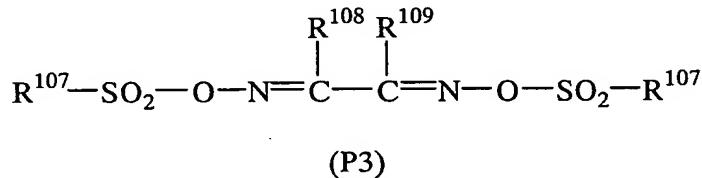
(P2)

Herein,  $R^{105}$  and  $R^{106}$  independently represent straight, branched or cyclic alkyl or halogenated alkyl groups of 1 to 12 carbon atoms, aryl or halogenated aryl groups of 6 to 20 carbon atoms, or aralkyl groups of 7 to 12 carbon atoms.

Of the groups represented by  $R^{105}$  and  $R^{106}$ , exemplary alkyl groups include methyl, ethyl, propyl, isopropyl, n-butyl, sec-butyl, tert-butyl, pentyl, hexyl, heptyl, octyl, amyl, cyclopentyl, cyclohexyl, cycloheptyl, norbornyl, and adamantyl. Exemplary halogenated alkyl groups include trifluoromethyl, 1,1,1-trifluoroethyl, 1,1,1-trichloroethyl, and nonafluorobutyl. Exemplary aryl groups include phenyl; alkoxyphenyl groups such as p-methoxyphenyl, m-methoxyphenyl, o-methoxyphenyl, ethoxyphenyl, p-tert-butoxyphenyl, and m-tert-butoxyphenyl; and alkylphenyl groups such as 2-methylphenyl, 3-methylphenyl, 4-methylphenyl, ethylphenyl,

4-*tert*-butylphenyl, 4-butylphenyl, and dimethylphenyl. Exemplary halogenated aryl groups include fluorophenyl, chlorophenyl, and 1,2,3,4,5-pentafluorophenyl. Exemplary aralkyl groups include benzyl and phenethyl.

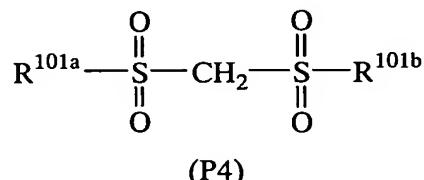
5 (iii) Glyoxime derivatives of formula (P3)



Herein,  $\text{R}^{107}$ ,  $\text{R}^{108}$ , and  $\text{R}^{109}$  independently represent straight, branched or cyclic alkyl or halogenated alkyl groups of 1 to 12 carbon atoms, aryl or halogenated aryl groups of 6 to 20 carbon atoms, or aralkyl groups of 7 to 12 carbon atoms. Also,  $\text{R}^{108}$  and  $\text{R}^{109}$ , taken together, may form a ring.  $\text{R}^{108}$  and  $\text{R}^{109}$  each are straight or branched alkylene groups of 1 to 6 carbon atoms when they form a ring.

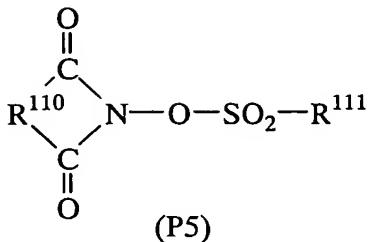
Illustrative examples of the alkyl, halogenated alkyl, aryl, halogenated aryl, and aralkyl groups represented by  $\text{R}^{107}$ ,  $\text{R}^{108}$ , and  $\text{R}^{109}$  are the same as exemplified for  $\text{R}^{105}$  and  $\text{R}^{106}$ . Examples of the alkylene groups represented by  $\text{R}^{108}$  and  $\text{R}^{109}$  include methylene, ethylene, propylene, butylene, and hexylene.

20 (iv) Bissulfone derivatives of formula (P4)



Herein,  $\text{R}^{101a}$  and  $\text{R}^{101b}$  are as defined above.

(v) Sulfonic acid esters of N-hydroxyimide compounds of formula (P5)



Herein,  $\text{R}^{110}$  is an arylene group of 6 to 10 carbon atoms, alkylene group of 1 to 6 carbon atoms, or alkenylene group of 2 to 6 carbon atoms wherein some or all of the hydrogen atoms may be replaced by straight or branched alkyl or alkoxy groups of 1 to 4 carbon atoms, nitro, acetyl, or phenyl groups.  $\text{R}^{111}$  is a straight, branched or cyclic alkyl group of 1 to 8 carbon atoms, alkenyl, alkoxyalkyl, phenyl or naphthyl group wherein some or all of the hydrogen atoms may be replaced by alkyl or alkoxy groups of 1 to 4 carbon atoms, phenyl groups (which may have substituted thereon an alkyl or alkoxy of 1 to 4 carbon atoms, nitro, or acetyl group), hetero-aromatic groups of 3 to 5 carbon atoms, or chlorine or fluorine atoms.

Of the groups represented by  $\text{R}^{110}$ , exemplary arylene groups include 1,2-phenylene and 1,8-naphthylene; exemplary alkylene groups include methylene, ethylene, trimethylene, tetramethylene, phenylethylene, and norbornane-2,3-diyl; and exemplary alkenylene groups include 1,2-vinylene, 1-phenyl-1,2-vinylene, and 5-norbornene-2,3-diyl. Of the groups represented by  $\text{R}^{111}$ , exemplary alkyl groups are as exemplified for  $\text{R}^{101a}$  to  $\text{R}^{101c}$ ; exemplary alkenyl groups include vinyl, 1-propenyl, allyl, 1-butenyl, 3-butenyl, isoprenyl, 1-pentenyl, 3-pentenyl, 4-pentenyl, dimethylallyl, 1-hexenyl, 3-hexenyl, 5-hexenyl, 1-heptenyl, 3-heptenyl, 6-heptenyl, and 7-octenyl; and exemplary alkoxyalkyl groups include methoxymethyl, ethoxymethyl, propoxymethyl, butoxymethyl, pentyloxymethyl, hexyloxymethyl, heptyloxymethyl, methoxyethyl, ethoxyethyl, propoxyethyl, butoxyethyl, pentyloxyethyl, hexyloxyethyl, methoxypropyl, ethoxypropyl,

propoxypropyl, butoxypropyl, methoxybutyl, ethoxybutyl, propoxybutyl, methoxypentyl, ethoxypentyl, methoxyhexyl, and methoxyheptyl.

Of the substituents on these groups, the alkyl groups  
5 of 1 to 4 carbon atoms include methyl, ethyl, propyl,  
isopropyl, n-butyl, isobutyl and tert-butyl; and the alkoxy  
groups of 1 to 4 carbon atoms include methoxy, ethoxy,  
propoxy, isopropoxy, n-butoxy, isobutoxy, and tert-butoxy.  
The phenyl groups which may have substituted thereon an alkyl  
10 or alkoxy of 1 to 4 carbon atoms, nitro, or acetyl group  
include phenyl, tolyl, p-tert-butoxyphenyl, p-acetylphenyl  
and p-nitrophenyl. The hetero-aromatic groups of 3 to 5  
carbon atoms include pyridyl and furyl.

Illustrative examples of the photoacid generator  
15 include:

onium salts such as  
diphenyliodonium trifluoromethanesulfonate,  
(p-tert-butoxyphenyl)phenyliodonium trifluoromethanesulfonate,  
diphenyliodonium p-toluenesulfonate,  
20 (p-tert-butoxyphenyl)phenyliodonium p-toluenesulfonate,  
triphenylsulfonium trifluoromethanesulfonate,  
(p-tert-butoxyphenyl)diphenylsulfonium trifluoromethane-  
sulfonate,  
bis(p-tert-butoxyphenyl)phenylsulfonium trifluoromethane-  
25 sulfonate,  
tris(p-tert-butoxyphenyl)sulfonium trifluoromethanesulfonate,  
triphenylsulfonium p-toluenesulfonate,  
(p-tert-butoxyphenyl)diphenylsulfonium p-toluenesulfonate,  
bis(p-tert-butoxyphenyl)phenylsulfonium p-toluenesulfonate,  
30 tris(p-tert-butoxyphenyl)sulfonium p-toluenesulfonate,  
triphenylsulfonium nonafluorobutanesulfonate,  
triphenylsulfonium butanesulfonate,  
trimethylsulfonium trifluoromethanesulfonate,  
trimethylsulfonium p-toluenesulfonate,  
35 cyclohexylmethyl(2-oxocyclohexyl)sulfonium trifluoromethane-  
sulfonate,  
cyclohexylmethyl(2-oxocyclohexyl)sulfonium p-toluenesulfonate,

dimethylphenylsulfonium trifluoromethanesulfonate,  
dimethylphenylsulfonium p-toluenesulfonate,  
dicyclohexylphenylsulfonium trifluoromethanesulfonate,  
dicyclohexylphenylsulfonium p-toluenesulfonate,  
5 trinaphthylsulfonium trifluoromethanesulfonate,  
cyclohexylmethyl(2-oxocyclohexyl)sulfonium trifluoromethane-  
sulfonate,  
(2-norbornyl)methyl(2-oxocyclohexyl)sulfonium trifluoro-  
methanesulfonate,  
10 ethylenebis[methyl(2-oxocyclopentyl)sulfonium trifluoro-  
methanesulfonate], and  
1,2'-naphthylcarbonylmethyltetrahydrothiophenium triflate;  
diazomethane derivatives such as  
bis(benzenesulfonyl)diazomethane,  
15 bis(p-toluenesulfonyl)diazomethane,  
bis(xylenesulfonyl)diazomethane,  
bis(cyclohexylsulfonyl)diazomethane,  
bis(cyclopentylsulfonyl)diazomethane,  
bis(n-butylsulfonyl)diazomethane,  
20 bis(isobutylsulfonyl)diazomethane,  
bis(sec-butylsulfonyl)diazomethane,  
bis(n-propylsulfonyl)diazomethane,  
bis(isopropylsulfonyl)diazomethane,  
bis(tert-butylsulfonyl)diazomethane,  
25 bis(n-amylsulfonyl)diazomethane,  
bis(isoamylsulfonyl)diazomethane,  
bis(sec-amylsulfonyl)diazomethane,  
bis(tert-amylsulfonyl)diazomethane,  
1-cyclohexylsulfonyl-1-(tert-butylsulfonyl)diazomethane,  
30 1-cyclohexylsulfonyl-1-(tert-amylsulfonyl)diazomethane, and  
1-tert-amylsulfonyl-1-(tert-butylsulfonyl)diazomethane;  
glyoxime derivatives such as  
bis-O-(p-toluenesulfonyl)-α-dimethylglyoxime,  
bis-O-(p-toluenesulfonyl)-α-diphenylglyoxime,  
35 bis-O-(p-toluenesulfonyl)-α-dicyclohexylglyoxime,  
bis-O-(p-toluenesulfonyl)-2,3-pentanedioneglyoxime,

bis-O-(p-toluenesulfonyl)-2-methyl-3,4-pentanedioneglyoxime,  
bis-O-(n-butanesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(n-butanesulfonyl)- $\alpha$ -diphenylglyoxime,  
bis-O-(n-butanesulfonyl)- $\alpha$ -dicyclohexylglyoxime,  
5 bis-O-(n-butanesulfonyl)-2,3-pentanedioneglyoxime,  
bis-O-(n-butanesulfonyl)-2-methyl-3,4-pentanedioneglyoxime,  
bis-O-(methanesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(trifluoromethanesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(1,1,1-trifluoroethanesulfonyl)- $\alpha$ -dimethylglyoxime,  
10 bis-O-(tert-butanesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(perfluorooctanesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(cyclohexanesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(benzenesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(p-fluorobenzenesulfonyl)- $\alpha$ -dimethylglyoxime,  
15 bis-O-(p-tert-butylbenzenesulfonyl)- $\alpha$ -dimethylglyoxime,  
bis-O-(xenesulfonyl)- $\alpha$ -dimethylglyoxime, and  
bis-O-(camphorsulfonyl)- $\alpha$ -dimethylglyoxime;  
bissulfone derivatives such as  
bisnaphthylsulfonylmethane, bistrifluoromethylsulfonylmethane,  
20 bismethylsulfonylmethane, bisethylsulfonylmethane,  
bispropylsulfonylmethane, bisisopropylsulfonylmethane,  
bis-p-toluenesulfonylmethane, and bisbenzenesulfonylmethane;  
 $\beta$ -ketosulfone derivatives such as  
2-cyclohexylcarbonyl-2-(p-toluenesulfonyl)propane and  
25 2-isopropylcarbonyl-2-(p-toluenesulfonyl)propane;  
nitrobenzyl sulfonate derivatives such as  
2,6-dinitrobenzyl p-toluenesulfonate and  
2,4-dinitrobenzyl p-toluenesulfonate;  
sulfonic acid ester derivatives such as  
30 1,2,3-tris(methanesulfonyloxy)benzene,  
1,2,3-tris(trifluoromethanesulfonyloxy)benzene, and  
1,2,3-tris(p-toluenesulfonyloxy)benzene; and

sulfonic acid esters of N-hydroxyimides such as  
N-hydroxysuccinimide methanesulfonate,  
N-hydroxysuccinimide trifluoromethanesulfonate,  
N-hydroxysuccinimide ethanesulfonate,  
5 N-hydroxysuccinimide 1-propanesulfonate,  
N-hydroxysuccinimide 2-propanesulfonate,  
N-hydroxysuccinimide 1-pentanesulfonate,  
N-hydroxysuccinimide 1-octanesulfonate,  
N-hydroxysuccinimide p-toluenesulfonate,  
10 N-hydroxysuccinimide p-methoxybenzenesulfonate,  
N-hydroxysuccinimide 2-chloroethanesulfonate,  
N-hydroxysuccinimide benzenesulfonate,  
N-hydroxysuccinimide 2,4,6-trimethylbenzenesulfonate,  
N-hydroxysuccinimide 1-naphthalenesulfonate,  
15 N-hydroxysuccinimide 2-naphthalenesulfonate,  
N-hydroxy-2-phenylsuccinimide methanesulfonate,  
N-hydroxymaleimide methanesulfonate,  
N-hydroxymaleimide ethanesulfonate,  
N-hydroxy-2-phenylmaleimide methanesulfonate,  
20 N-hydroxyglutarimide methanesulfonate,  
N-hydroxyglutarimide benzenesulfonate,  
N-hydroxypthalimide methanesulfonate,  
N-hydroxypthalimide benzenesulfonate,  
N-hydroxypthalimide trifluoromethanesulfonate,  
25 N-hydroxypthalimide p-toluenesulfonate,  
N-hydroxynaphthalimide methanesulfonate,  
N-hydroxynaphthalimide benzenesulfonate,  
N-hydroxy-5-norbornene-2,3-dicarboxyimide methanesulfonate,  
N-hydroxy-5-norbornene-2,3-dicarboxyimide trifluoromethane-  
30 sulfonate, and  
N-hydroxy-5-norbornene-2,3-dicarboxyimide p-toluenesulfonate.

Preferred among these photoacid generators are onium salts such as triphenylsulfonium trifluoromethanesulfonate, (p-tert-butoxyphenyl)diphenylsulfonium trifluoromethane-sulfonate,  
35 tris(p-tert-butoxyphenyl)sulfonium trifluoromethanesulfonate, triphenylsulfonium p-toluenesulfonate,

(p-tert-butoxyphenyl)diphenylsulfonium p-toluenesulfonate,  
tris(p-tert-butoxyphenyl)sulfonium p-toluenesulfonate,  
trinaphthylsulfonium trifluoromethanesulfonate,  
cyclohexylmethyl(2-oxocyclohexyl)sulfonium trifluoromethane-  
5 sulfonate,  
(2-norbornyl)methyl(2-oxocylohexyl)sulfonium trifluoro-  
methanesulfonate, and  
1,2'-naphthylcarbonylmethyltetrahydrothiophenium triflate;  
diazomethane derivatives such as  
10 bis(benzenesulfonyl)diazomethane,  
bis(p-toluenesulfonyl)diazomethane,  
bis(cyclohexylsulfonyl)diazomethane,  
bis(n-butylsulfonyl)diazomethane,  
bis(isobutylsulfonyl)diazomethane,  
15 bis(sec-butylsulfonyl)diazomethane,  
bis(n-propylsulfonyl)diazomethane,  
bis(isopropylsulfonyl)diazomethane, and  
bis(tert-butylsulfonyl)diazomethane;  
glyoxime derivatives such as  
20 bis-O-(p-toluenesulfonyl)- $\alpha$ -dimethylglyoxime and  
bis-O-(n-butanesulfonyl)- $\alpha$ -dimethylglyoxime;  
bissulfone derivatives such as bisnaphthylsulfonylmethane;  
and sulfonic acid esters of N-hydroxyimide compounds such as  
N-hydroxysuccinimide methanesulfonate,  
25 N-hydroxysuccinimide trifluoromethanesulfonate,  
N-hydroxysuccinimide 1-propanesulfonate,  
N-hydroxysuccinimide 2-propanesulfonate,  
N-hydroxysuccinimide 1-pentanesulfonate,  
N-hydroxysuccinimide p-toluenesulfonate,  
30 N-hydroxynaphthalimide methanesulfonate, and  
N-hydroxynaphthalimide benzenesulfonate.

Also included are the oxime sulfonates described in  
USP 6,004,724, for example,  
(5-(4-toluenesulfonyl)oxyimino-5H-thiophen-2-ylidene)phenyl-  
35 acetonitrile,  
(5-(10-camphorsulfonyl)oxyimino-5H-thiophen-2-ylidene)phenyl-  
acetonitrile,

(5-n-octanesulfonyloxyimino-5H-thiophen-2-ylidene)phenyl-acetonitrile,

(5-(4-toluenesulfonyl)oxyimino-5H-thiophen-2-ylidene)(2-methylphenyl)acetonitrile,

5 (5-(10-camphorsulfonyl)oxyimino-5H-thiophen-2-ylidene)(2-methylphenyl)acetonitrile,

(5-n-octanesulfonyloxyimino-5H-thiophen-2-ylidene)(2-methylphenyl)acetonitrile; etc.

Also included are the oxime sulfonates described in

10 USP 6,261,738 and JP-A 2000-314956, for example,

2,2,2-trifluoro-1-phenyl-ethanone oxime-O-methylsulfonate;  
2,2,2-trifluoro-1-phenyl-ethanone oxime-O-(10-camphorylsulfonate);

15 2,2,2-trifluoro-1-phenyl-ethanone oxime-O-(4-methoxyphenyl-sulfonate);

2,2,2-trifluoro-1-phenyl-ethanone oxime-O-(1-naphthyl-sulfonate);

2,2,2-trifluoro-1-phenyl-ethanone oxime-O-(2-naphthyl-sulfonate);

20 2,2,2-trifluoro-1-phenyl-ethanone oxime-O-(2,4,6-trimethylphenylsulfonate);

2,2,2-trifluoro-1-(4-methylphenyl)-ethanone oxime-O-(10-camphorylsulfonate);

25 2,2,2-trifluoro-1-(4-methylphenyl)-ethanone oxime-O-(methylsulfonate);

2,2,2-trifluoro-1-(2-methylphenyl)-ethanone oxime-O-(10-camphorylsulfonate);

2,2,2-trifluoro-1-(2,4-dimethylphenyl)-ethanone oxime-O-(10-camphorylsulfonate);

30 2,2,2-trifluoro-1-(2,4-dimethylphenyl)-ethanone oxime-O-(1-naphthylsulfonate);

2,2,2-trifluoro-1-(2,4-dimethylphenyl)-ethanone oxime-O-(2-naphthylsulfonate);

35 2,2,2-trifluoro-1-(2,4,6-trimethylphenyl)-ethanone oxime-O-(10-camphorylsulfonate);

2,2,2-trifluoro-1-(2,4,6-trimethylphenyl)-ethanone oxime-O-(1-naphthylsulfonate);

2,2,2-trifluoro-1-(2,4,6-trimethylphenyl)-ethanone oxime-O-(2-naphthylsulfonate);  
2,2,2-trifluoro-1-(4-methoxyphenyl)-ethanone oxime-O-methylsulfonate;  
5 2,2,2-trifluoro-1-(4-methylthiophenyl)-ethanone oxime-O-methylsulfonate;  
2,2,2-trifluoro-1-(3,4-dimethoxyphenyl)-ethanone oxime-O-methylsulfonate;  
10 2,2,3,3,4,4-heptafluoro-1-phenyl-butanone oxime-O-(10-camphorylsulfonate);  
2,2,2-trifluoro-1-(phenyl)-ethanone oxime-O-methylsulfonate;  
2,2,2-trifluoro-1-(phenyl)-ethanone oxime-O-10-camphorylsulfonate;  
15 2,2,2-trifluoro-1-(phenyl)-ethanone oxime-O-(4-methoxy-phenyl)sulfonate;  
2,2,2-trifluoro-1-(phenyl)-ethanone oxime-O-(1-naphthyl)sulfonate;  
2,2,2-trifluoro-1-(phenyl)-ethanone oxime-O-(2-naphthyl)sulfonate;  
20 2,2,2-trifluoro-1-(phenyl)-ethanone oxime-O-(2,4,6-trimethyl-phenyl)sulfonate;  
2,2,2-trifluoro-1-(4-methylphenyl)-ethanone oxime-O-(10-camphoryl)sulfonate;  
2,2,2-trifluoro-1-(4-methylphenyl)-ethanone oxime-O-methylsulfonate;  
25 2,2,2-trifluoro-1-(2-methylphenyl)-ethanone oxime-O-(10-camphoryl)sulfonate;  
2,2,2-trifluoro-1-(2,4-dimethylphenyl)-ethanone oxime-O-(1-naphthyl)sulfonate;  
30 2,2,2-trifluoro-1-(2,4-dimethylphenyl)-ethanone oxime-O-(2-naphthyl)sulfonate;  
2,2,2-trifluoro-1-(2,4,6-trimethylphenyl)-ethanone oxime-O-(10-camphoryl)sulfonate;  
35 2,2,2-trifluoro-1-(2,4,6-trimethylphenyl)-ethanone oxime-O-(1-naphthyl)sulfonate;  
2,2,2-trifluoro-1-(2,4,6-trimethylphenyl)-ethanone oxime-O-(2-naphthyl)sulfonate;

2,2,2-trifluoro-1-(4-methoxyphenyl)-ethanone oxime-O-methylsulfonate;

2,2,2-trifluoro-1-(4-thiomethylphenyl)-ethanone oxime-O-methylsulfonate;

5 2,2,2-trifluoro-1-(3,4-dimethoxyphenyl)-ethanone oxime-O-methylsulfonate;

2,2,2-trifluoro-1-(4-methoxyphenyl)-ethanone oxime-O-(4-methylphenyl)sulfonate;

10 2,2,2-trifluoro-1-(4-methoxyphenyl)-ethanone oxime-O-(4-methoxyphenyl)sulfonate;

2,2,2-trifluoro-1-(4-methoxyphenyl)-ethanone oxime-O-(4-dodecylphenyl)sulfonate;

2,2,2-trifluoro-1-(4-methoxyphenyl)-ethanone oxime-O-octylsulfonate;

15 2,2,2-trifluoro-1-(4-thiomethylphenyl)-ethanone oxime-O-(4-methoxyphenyl)sulfonate;

2,2,2-trifluoro-1-(4-thiomethylphenyl)-ethanone oxime-O-(4-dodecylphenyl)sulfonate;

2,2,2-trifluoro-1-(4-thiomethylphenyl)-ethanone oxime-O-

20 octylsulfonate;

2,2,2-trifluoro-1-(4-thiomethylphenyl)-ethanone oxime-O-(2-naphthyl)sulfonate;

2,2,2-trifluoro-1-(2-methylphenyl)-ethanone oxime-O-methylsulfonate;

25 2,2,2-trifluoro-1-(4-methylphenyl)ethanone oxime-O-phenylsulfonate;

2,2,2-trifluoro-1-(4-chlorophenyl)-ethanone oxime-O-phenylsulfonate;

2,2,3,3,4,4-heptafluoro-1-(phenyl)-butanone oxime-O-(10-

30 camphoryl)sulfonate;

2,2,2-trifluoro-1-naphthyl-ethanone oxime-O-methylsulfonate;

2,2,2-trifluoro-2-naphthyl-ethanone oxime-O-methylsulfonate;

2,2,2-trifluoro-1-[4-benzylphenyl]-ethanone oxime-O-methylsulfonate;

35 2,2,2-trifluoro-1-[4-(phenyl-1,4-dioxa-but-1-yl)phenyl]-ethanone oxime-O-methylsulfonate;

2,2,2-trifluoro-1-naphthyl-ethanone oxime-O-propylsulfonate;

2,2,2-trifluoro-2-naphthyl-ethanone oxime-O-propylsulfonate;  
2,2,2-trifluoro-1-[4-benzylphenyl]-ethanone oxime-O-propyl-  
sulfonate;  
2,2,2-trifluoro-1-[4-methylsulfonylphenyl]-ethanone oxime-O-  
5 propylsulfonate;  
1,3-bis[1-(4-phenoxyphenyl)-2,2,2-trifluoroethanone oxime-O-  
sulfonyl]phenyl;  
2,2,2-trifluoro-1-[4-methylsulfonyloxyphenyl]-ethanone oxime-  
O-propylsulfonate;  
10 2,2,2-trifluoro-1-[4-methylcarbonyloxyphenyl]-ethanone oxime-  
O-propylsulfonate;  
2,2,2-trifluoro-1-[6H,7H-5,8-dioxonaphth-2-yl]-ethanone  
oxime-O-propylsulfonate;  
2,2,2-trifluoro-1-[4-methoxycarbonylmethoxyphenyl]-ethanone  
15 oxime-O-propylsulfonate;  
2,2,2-trifluoro-1-[4-(methoxycarbonyl)-(4-amino-1-oxa-pent-1-  
y1)-phenyl]-ethanone oxime-O-propylsulfonate;  
2,2,2-trifluoro-1-[3,5-dimethyl-4-ethoxyphenyl]-ethanone  
oxime-O-propylsulfonate;  
20 2,2,2-trifluoro-1-[4-benzyloxyphenyl]-ethanone oxime-O-  
propylsulfonate;  
2,2,2-trifluoro-1-[2-thiophenyl]-ethanone oxime-O-propyl-  
sulfonate; and  
2,2,2-trifluoro-1-[1-dioxa-thiophen-2-yl])-ethanone oxime-O-  
25 propylsulfonate.

Also included are the oxime sulfonates described in  
JP-A 9-95479 and JP-A 9-230588 and the references cited  
therein, for example,

α-(p-toluenesulfonyloxyimino)-phenylacetonitrile,  
30 α-(p-chlorobenzenesulfonyloxyimino)-phenylacetonitrile,  
α-(4-nitrobenzenesulfonyloxyimino)-phenylacetonitrile,  
α-(4-nitro-2-trifluoromethylbenzenesulfonyloxyimino)-  
phenylacetonitrile,  
α-(benzenesulfonyloxyimino)-4-chlorophenylacetonitrile,  
35 α-(benzenesulfonyloxyimino)-2,4-dichlorophenylacetonitrile,

$\alpha$ -(benzenesulfonyloxyimino)-2,6-dichlorophenylacetonitrile,  
 $\alpha$ -(benzenesulfonyloxyimino)-4-methoxyphenylacetonitrile,  
 $\alpha$ -(2-chlorobenzenesulfonyloxyimino)-4-methoxyphenyl-  
acetonitrile,  
5    $\alpha$ -(benzenesulfonyloxyimino)-2-thienylacetonitrile,  
 $\alpha$ -(4-dodecylbenzenesulfonyloxyimino)-phenylacetonitrile,  
 $\alpha$ -[(4-toluenesulfonyloxyimino)-4-methoxyphenyl]acetonitrile,  
 $\alpha$ -[(dodecylbenzenesulfonyloxyimino)-4-methoxyphenyl]-  
acetonitrile,  
10    $\alpha$ -(tosyloxyimino)-3-thienylacetonitrile,  
 $\alpha$ -(methylsulfonyloxyimino)-1-cyclopentenylacetonitrile,  
 $\alpha$ -(ethylsulfonyloxyimino)-1-cyclopentenylacetonitrile,  
 $\alpha$ -(isopropylsulfonyloxyimino)-1-cyclopentenylacetonitrile,  
 $\alpha$ -(n-butylsulfonyloxyimino)-1-cyclopentenylacetonitrile,  
15    $\alpha$ -(ethylsulfonyloxyimino)-1-cyclohexenylacetonitrile,  
 $\alpha$ -(isopropylsulfonyloxyimino)-1-cyclohexenylacetonitrile, and  
 $\alpha$ -(n-butylsulfonyloxyimino)-1-cyclohexenylacetonitrile.  
            Suitable bisoxime sulfonates include those described  
in JP-A 9-208554, for example,  
20   bis( $\alpha$ -(4-toluenesulfonyloxy)imino)-p-phenylenediacetonitrile,  
      bis( $\alpha$ -(benzenesulfonyloxy)imino)-p-phenylenediacetonitrile,  
      bis( $\alpha$ -(methanesulfonyloxy)imino)-p-phenylenediacetonitrile,  
      bis( $\alpha$ -(butanesulfonyloxy)imino)-p-phenylenediacetonitrile,  
      bis( $\alpha$ -(10-camphorsulfonyloxy)imino)-p-phenylenediaceto-  
25   nitrile,  
      bis( $\alpha$ -(4-toluenesulfonyloxy)imino)-p-phenylenediacetonitrile,  
      bis( $\alpha$ -(trifluoromethanesulfonyloxy)imino)-p-phenylenediaceto-  
nitrile,  
      bis( $\alpha$ -(4-methoxybenzenesulfonyloxy)imino)-p-phenylenediaceto-  
30   nitrile,  
      bis( $\alpha$ -(4-toluenesulfonyloxy)imino)-m-phenylenediacetonitrile,

bis( $\alpha$ -(benzenesulfonyloxy)imino)-m-phenylenediacetonitrile,  
bis( $\alpha$ -(methanesulfonyloxy)imino)-m-phenylenediacetonitrile,  
bis( $\alpha$ -(butanesulfonyloxy)imino)-m-phenylenediacetonitrile,  
bis( $\alpha$ -(10-camphorsulfonyloxy)imino)-m-phenylenediaceto-  
5 nitrile,  
bis( $\alpha$ -(4-toluenesulfonyloxy)imino)-m-phenylenediacetonitrile,  
bis( $\alpha$ -(trifluoromethanesulfonyloxy)imino)-m-phenylenediaceto-  
nitrile,  
bis( $\alpha$ -(4-methoxybenzenesulfonyloxy)imino)-m-phenylenediaceto-  
10 nitrile, etc.

These photoacid generators may be used singly or in combinations of two or more thereof. Onium salts are effective for improving rectangularity, while diazomethane derivatives and glyoxime derivatives are effective for reducing standing waves. The combination of an onium salt with a diazomethane or a glyoxime derivative allows for fine adjustment of the profile.

The photoacid generator is added in an amount of 0.1 to 50 parts, and especially 0.5 to 40 parts by weight, per 20 100 parts by weight of the base resin. Less than 0.1 part of the photoacid generator may generate a less amount of acid upon exposure, sometimes leading to a poor sensitivity and resolution whereas more than 50 parts of the photoacid generator may adversely affect the transmittance and 25 resolution of resist.

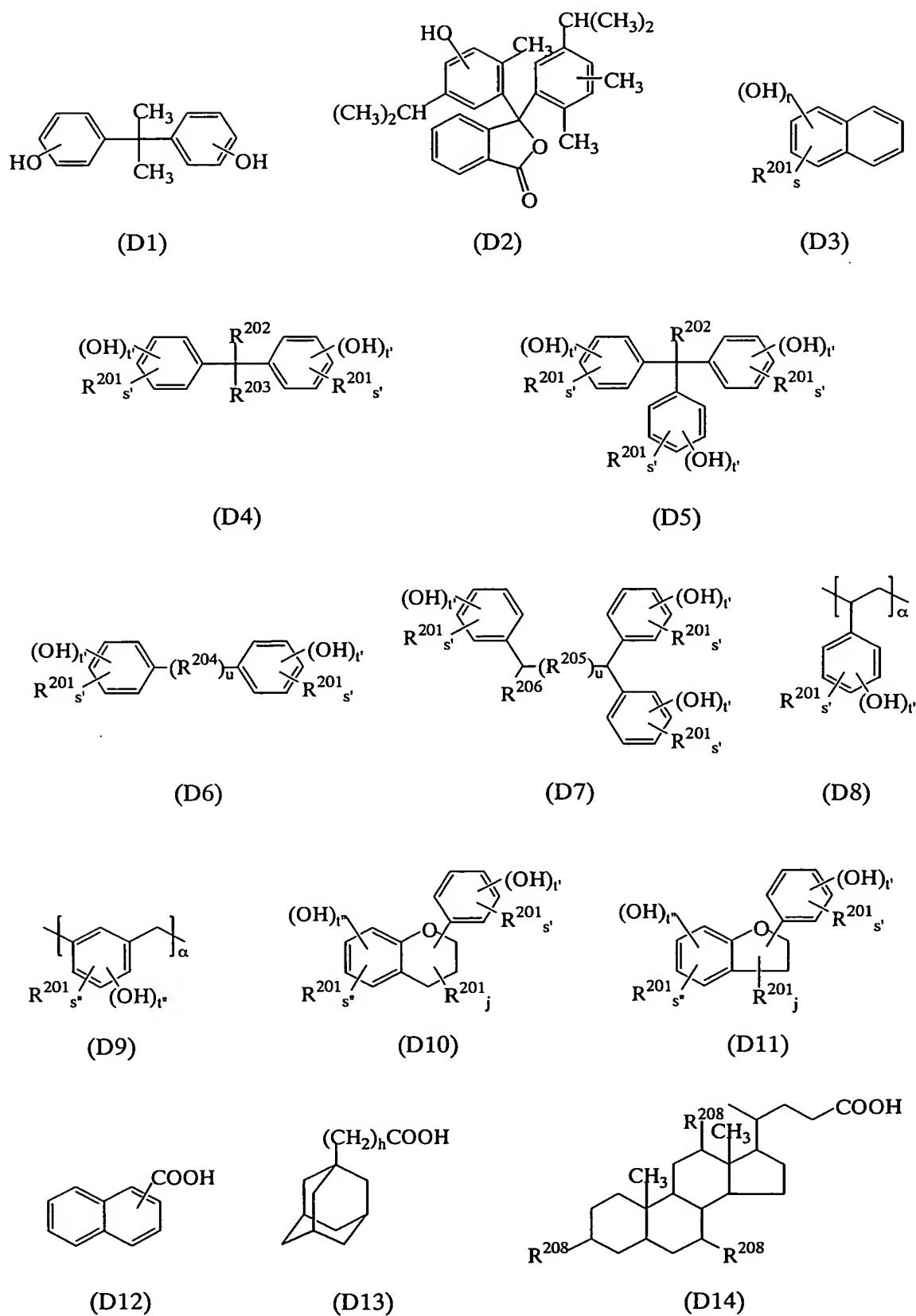
(E) Dissolution inhibitor

To the resist composition, a dissolution inhibitor may be added. The dissolution inhibitor is a compound having on the molecule at least two phenolic hydroxyl groups, in which 30 an average of from 0 to 100 mol% of all the hydrogen atoms on the phenolic hydroxyl groups are replaced with acid labile groups or a compound having on the molecule at least one carboxyl group, in which an average of 50 to 100 mol% of all the hydrogen atoms on the carboxyl groups are replaced with 35 acid labile groups, both the compounds having an average

molecular weight within a range of 100 to 1,000, and preferably 150 to 800.

The degree of substitution of the hydrogen atoms on the phenolic hydroxyl groups with acid labile groups is on average at least 0 mol%, and preferably at least 30 mol%, of all the phenolic hydroxyl groups. The upper limit is 100 mol%, and preferably 80 mol%. The degree of substitution of the hydrogen atoms on the carboxyl groups with acid labile groups is on average at least 50 mol%, and preferably at least 70 mol%, of all the carboxyl groups, with the upper limit being 100 mol%.

Preferable examples of such compounds having two or more phenolic hydroxyl groups or compounds having at least one carboxyl group include those of formulas (D1) to (D14) below.



In these formulas, R<sup>201</sup> and R<sup>202</sup> are each hydrogen or a straight or branched alkyl or alkenyl of 1 to 8 carbon atoms; R<sup>203</sup> is hydrogen, a straight or branched alkyl or alkenyl of 1 to 8 carbon atoms, or -(R<sup>207</sup>)<sub>h</sub>-COOH; R<sup>204</sup> is -(CH<sub>2</sub>)<sub>i</sub>- (where i = 5 to 10), an arylene of 6 to 10 carbon atoms, carbonyl, sulfonyl, an oxygen atom, or a sulfur atom; R<sup>205</sup> is an alkylene of 1 to 10 carbon atoms, an arylene of 6 to 10 carbon atoms, carbonyl, sulfonyl, an oxygen atom, or a sulfur atom; R<sup>206</sup> is hydrogen, a straight or branched alkyl or 10 alkenyl of 1 to 8 carbon atoms, or a hydroxyl-substituted phenyl or naphthyl; R<sup>207</sup> is a straight or branched alkylene of 1 to 10 carbon atoms; R<sup>208</sup> is hydrogen or hydroxyl; the letter j is an integer from 0 to 5; u and h are each 0 or 1; s, t, s', t', s'', and t'' are each numbers which satisfy s+t = 8, 15 s'+t' = 5, and s''+t'' = 4, and are such that each phenyl skeleton has at least one hydroxyl group; and  $\alpha$  is a number such that the compounds of formula (D8) or (D9) have a molecular weight of from 100 to 1,000.

The above compounds have a weight average molecular 20 weight within a range of 100 to 1,000, and preferably 150 to 800.

The dissolution inhibitor may be formulated in an amount of 0 to 50 parts, preferably 5 to 50 parts, and more 25 preferably 10 to 30 parts by weight, per 100 parts by weight of the base resin, and may be used singly or as a mixture of two or more thereof. Too less an amount of the dissolution inhibitor may fail to improve resolution whereas the use of more than 50 parts may lead to slimming of the patterned film, and thus a decline in resolution.

30 (F) Crosslinker

Formulated in the negative resist composition is a crosslinker (F) which forms a crosslinked structure under the action of acid. Typical crosslinkers are compounds having at least two hydroxymethyl, alkoxyethyl, epoxy or vinyl ether 35 groups within a molecule. Substituted glycoluril derivatives, urea derivatives, and hexa(methoxymethyl)melamine compounds are suitable as the crosslinker. Examples include

N,N,N',N'-tetramethoxymethylurea, hexamethylenimine,  
tetraalkoxymethyl-substituted glycoluril compounds such as  
tetrahydroxymethyl-substituted glycoluril and  
tetramethoxymethylglycoluril, and condensates of phenolic  
5 compounds such as substituted or unsubstituted  
bis(hydroxymethylphenol) compounds and bisphenol A with  
epichlorohydrin. Especially preferred crosslinkers are  
1,3,5,7-tetraalkoxymethylglycolurils such as  
1,3,5,7-tetramethoxymethylglycoluril,  
10 1,3,5,7-tetrahydroxymethylglycoluril,  
2,6-dihydroxymethyl-p-cresol, 2,6-dihydroxymethylphenol,  
2,2',6,6'-tetrahydroxymethyl-bisphenol A,  
1,4-bis[2-(2-hydroxypropyl)]benzene,  
N,N,N',N'-tetramethoxymethylurea, and  
15 hexamethoxymethylmelamine. In the resist composition, an  
appropriate amount of the crosslinker is, though not limited  
thereto, about 1 to 25 parts, and especially about 5 to 20  
parts by weight per 100 parts by weight of the base resin in  
the composition. The crosslinkers may be used alone or in  
20 admixture of two or more.

In addition to the inventive basic compound, one or  
more of commonly used basic compounds may be employed in the  
inventive resist composition. Examples of suitable  
conventional basic compounds include primary, secondary, and  
25 tertiary aliphatic amines, mixed amines, aromatic amines,  
heterocyclic amines, carboxyl group-bearing nitrogenous  
compounds, sulfonyl group-bearing nitrogenous compounds,  
hydroxyl group-bearing nitrogenous compounds, hydroxyphenyl  
group-bearing nitrogenous compounds, alcoholic nitrogenous  
30 compounds, amide derivatives, and imide derivatives.

Examples of suitable primary aliphatic amines include  
ammonia, methylamine, ethylamine, n-propylamine,  
isopropylamine, n-butylamine, iso-butylamine, sec-butylamine,  
tert-butylamine, pentylamine, tert-amylamine,  
35 cyclopentylamine, hexylamine, cyclohexylamine, heptylamine,  
octylamine, nonylamine, decylamine, dodecylamine, cetylamine,  
methylenediamine, ethylenediamine, and tetraethylenepentamine.

Examples of suitable secondary aliphatic amines include dimethylamine, diethylamine, di-n-propylamine, di-iso-propylamine, di-n-butylamine, di-iso-butylamine, di-sec-butylamine, dipentylamine, dicyclopentylamine, 5 dihexylamine, dicyclohexylamine, diheptylamine, dioctylamine, dinonylamine, didecylamine, didodecylamine, dicetylamine, N,N-dimethylmethylenediamine, N,N-dimethylethylenediamine, and N,N-dimethyltetraethylenepentamine. Examples of suitable 10 tertiary aliphatic amines include trimethylamine, triethylamine, tri-n-propylamine, tri-iso-propylamine, tri-n-butylamine, tri-iso-butylamine, tri-sec-butylamine, tripentylamine, tricyclopentylamine, trihexylamine, tricyclohexylamine, triheptylamine, trioctylamine, trinonylamine, tridecylamine, tridodecylamine, tricetylamine, 15 N,N,N',N'-tetramethylmethylenediamine, N,N,N',N'-tetramethylethylenediamine, and N,N,N',N'-tetramethyltetraethylenepentamine.

Examples of suitable mixed amines include dimethylethylamine, methylethylpropylamine, benzylamine, 20 phenethylamine, and benzylidemethylamine. Examples of suitable aromatic and heterocyclic amines include aniline derivatives (e.g., aniline, N-methylaniline, N-ethylaniline, N-propylaniline, N,N-dimethylaniline, 2-methylaniline, 3-methylaniline, 4-methylaniline, ethylaniline, propylaniline, 25 trimethylaniline, 2-nitroaniline, 3-nitroaniline, 4-nitroaniline, 2,4-dinitroaniline, 2,6-dinitroaniline, 3,5-dinitroaniline, and N,N-dimethyltoluidine), diphenyl(p-tolyl)amine, methyldiphenylamine, triphenylamine, phenylenediamine, naphthylamine, diaminonaphthalene, 30 pyrrole derivatives (e.g., pyrrole, 2H-pyrrole, 1-methylpyrrole, 2,4-dimethylpyrrole, 2,5-dimethylpyrrole, and N-methylpyrrole), oxazole derivatives (e.g., oxazole and isooxazole), thiazole derivatives (e.g., thiazole and isothiazole), imidazole derivatives (e.g., imidazole, 35 4-methylimidazole, and 4-methyl-2-phenylimidazole), pyrazole derivatives, furazan derivatives, pyrrolidine derivatives (e.g., pyrrolidine and

2-methyl-1-pyrroline), pyrrolidine derivatives (e.g.,  
pyrrolidine, N-methylpyrrolidine, pyrrolidinone, and  
N-methylpyrrolidone), imidazoline derivatives, imidazolidine  
derivatives, pyridine derivatives (e.g., pyridine,  
5 methylpyridine, ethylpyridine, propylpyridine, butylpyridine,  
4-(1-butylpentyl)pyridine, dimethylpyridine,  
trimethylpyridine, triethylpyridine, phenylpyridine,  
3-methyl-2-phenylpyridine, 4-tert-butylpyridine,  
diphenylpyridine, benzylpyridine, methoxypyridine,  
10 buutoxypyridine, dimethoxypyridine, 1-methyl-2-pyridone,  
4-pyrrolidinopyridine, 1-methyl-4-phenylpyridine,  
2-(1-ethylpropyl)pyridine, aminopyridine, and  
dimethylaminopyridine), pyridazine derivatives,  
pyrimidine derivatives, pyrazine derivatives,  
15 pyrazoline derivatives, pyrazolidine derivatives,  
piperidine derivatives, piperazine derivatives,  
morpholine derivatives, indole derivatives,  
isoindole derivatives, 1H-indazole derivatives,  
indoline derivatives, quinoline derivatives (e.g., quinoline  
20 and 3-quinolinecarbonitrile), isoquinoline derivatives,  
cinnoline derivatives, quinazoline derivatives,  
quinoxaline derivatives, phthalazine derivatives,  
purine derivatives, pteridine derivatives,  
carbazole derivatives, phenanthridine derivatives,  
25 acridine derivatives, phenazine derivatives,  
1,10-phenanthroline derivatives, adenine derivatives,  
adenosine derivatives, guanine derivatives,  
guanosine derivatives, uracil derivatives, and  
uridine derivatives.

30 Examples of suitable carboxyl group-bearing  
nitrogenous compounds include aminobenzoic acid,  
indolecarboxylic acid, and amino acid derivatives  
(e.g. nicotinic acid, alanine, alginine, aspartic acid,  
glutamic acid, glycine, histidine, isoleucine, glycylleucine,  
35 leucine, methionine, phenylalanine, threonine, lysine,  
3-amino pyrazine-2-carboxylic acid, and methoxyalanine).

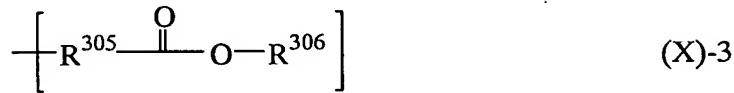
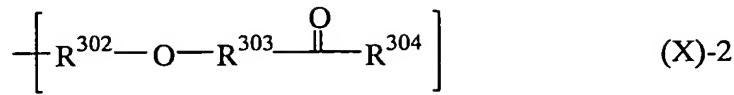
Examples of suitable sulfonyl group-bearing nitrogenous compounds include 3-pyridinesulfonic acid and pyridinium p-toluenesulfonate. Examples of suitable hydroxyl group-bearing nitrogenous compounds, hydroxyphenyl group-bearing nitrogenous compounds, and alcoholic nitrogenous compounds include 2-hydroxypyridine, aminocresol, 2,4-quinolinediol, monoethanolamine, diethanolamine, triethanolamine, N-ethyl diethanolamine, N,N-diethylethanolamine, triisopropanolamine, 2,2'-iminodiethanol, 2-aminoethanol, 3-amino-1-propanol, 4-amino-1-butanol, 4-(2-hydroxyethyl)morpholine, 2-(2-hydroxyethyl)pyridine, 1-(2-hydroxyethyl)piperazine, 1-[2-(2-hydroxyethoxy)ethyl]piperazine, piperidine ethanol, 1-(2-hydroxyethyl)pyrrolidine, 1-(2-hydroxyethyl)-2-pyrrolidinone, 3-piperidino-1,2-propanediol, 3-pyrrolidino-1,2-propanediol, 8-hydroxyjulolidine, 3-quinuclidinol, 3-tropanol, 1-methyl-2-pyrrolidine ethanol, 1-aziridine ethanol, N-(2-hydroxyethyl)phthalimide, and

20 N-(2-hydroxyethyl)isonicotinamide. Examples of suitable amide derivatives include formamide, N-methylformamide, N,N-dimethylformamide, acetamide, N-methylacetamide, N,N-dimethylacetamide, propionamide, and benzamide. Suitable imide derivatives include phthalimide, succinimide, and maleimide.

In addition, basic compounds of the following general formula (B)-1 may also be included alone or in admixture.



30 In the formula, n is equal to 1, 2 or 3; side chain Y is independently hydrogen or a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain an ether or hydroxyl group; and side chain X is independently selected from groups of the following general formulas (X)-1 to (X)-3, and two or three X's may bond together to form a ring.



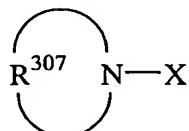
In the formulas,  $R^{300}$ ,  $R^{302}$  and  $R^{305}$  are independently straight or branched alkylene groups of 1 to 4 carbon atoms;  $R^{301}$  and  $R^{304}$  are independently hydrogen, straight, branched or 5 cyclic alkyl groups of 1 to 20 carbon atoms, which may contain at least one hydroxyl, ether, ester group or lactone ring;  $R^{303}$  is a single bond or a straight or branched alkylene group of 1 to 4 carbon atoms; and  $R^{306}$  is a straight, branched 10 or cyclic alkyl group of 1 to 20 carbon atoms, which may contain at least one hydroxyl, ether, ester group or lactone ring.

Illustrative examples of the basic compounds of formula (B)-1 include tris(2-methoxymethoxyethyl)amine, tris{2-(2-methoxyethoxy)ethyl}amine,  
15 tris{2-(2-methoxyethoxymethoxy)ethyl}amine, tris{2-(1-methoxyethoxy)ethyl}amine, tris{2-(1-ethoxyethoxy)ethyl}amine, tris{2-(1-ethoxypropoxy)ethyl}amine, tris[2-{2-(2-hydroxyethoxy)ethoxy}ethyl]amine,  
20 4,7,13,16,21,24-hexaoxa-1,10-diazabicyclo[8.8.8]hexacosane, 4,7,13,18-tetraoxa-1,10-diazabicyclo[8.5.5]eicosane, 1,4,10,13-tetraoxa-7,16-diazabicyclooctadecane, 1-aza-12-crown-4, 1-aza-15-crown-5, 1-aza-18-crown-6, tris(2-formyloxyethyl)amine, tris(2-acetoxyethyl)amine,  
25 tris(2-propionyloxyethyl)amine, tris(2-butyryloxyethyl)amine, tris(2-isobutyryloxyethyl)amine, tris(2-valeryloxyethyl)amine, tris(2-pivaloyloxyethyl)amine, N,N-bis(2-acetoxyethyl)-2-(acetoxyacetoxyl)ethylamine, tris(2-methoxycarbonyloxyethyl)amine,

tris(2-tert-butoxycarbonyloxyethyl)amine,  
tris[2-(2-oxopropoxy)ethyl]amine,  
tris[2-(methoxycarbonylmethyl)oxyethyl]amine,  
tris[2-(tert-butoxycarbonylmethyloxy)ethyl]amine,  
5 tris[2-(cyclohexyloxycarbonylmethyloxy)ethyl]amine,  
tris(2-methoxycarbonylethyl)amine,  
tris(2-ethoxycarbonylethyl)amine,  
N,N-bis(2-hydroxyethyl)-2-(methoxycarbonyl)ethylamine,  
N,N-bis(2-acetoxyethyl)-2-(methoxycarbonyl)ethylamine,  
10 N,N-bis(2-hydroxyethyl)-2-(ethoxycarbonyl)ethylamine,  
N,N-bis(2-acetoxyethyl)-2-(ethoxycarbonyl)ethylamine,  
N,N-bis(2-hydroxyethyl)-2-(2-methoxyethoxycarbonyl)ethylamine,  
N,N-bis(2-acetoxyethyl)-2-(2-methoxyethoxycarbonyl)ethylamine,  
N,N-bis(2-hydroxyethyl)-2-(2-hydroxyethoxycarbonyl)ethylamine,  
15 N,N-bis(2-acetoxyethyl)-2-(2-acetoxyethoxycarbonyl)ethylamine,  
N,N-bis(2-hydroxyethyl)-2-[(methoxycarbonyl)methoxycarbonyl]-  
ethylamine,  
N,N-bis(2-acetoxyethyl)-2-[(methoxycarbonyl)methoxycarbonyl]-  
ethylamine,  
20 N,N-bis(2-hydroxyethyl)-2-(2-oxopropoxycarbonyl)ethylamine,  
N,N-bis(2-acetoxyethyl)-2-(2-oxopropoxycarbonyl)ethylamine,  
N,N-bis(2-hydroxyethyl)-2-(tetrahydrofurfuryloxycarbonyl)-  
ethylamine,  
N,N-bis(2-acetoxyethyl)-2-(tetrahydrofurfuryloxycarbonyl)-  
25 ethylamine,  
N,N-bis(2-hydroxyethyl)-2-[(2-oxotetrahydrofuran-3-yl)oxygeno-  
carbonyl]ethylamine,  
N,N-bis(2-acetoxyethyl)-2-[(2-oxotetrahydrofuran-3-yl)oxygeno-  
carbonyl]ethylamine,  
30 N,N-bis(2-hydroxyethyl)-2-(4-hydroxybutoxycarbonyl)ethylamine,  
N,N-bis(2-formyloxyethyl)-2-(4-formyloxybutoxycarbonyl)-  
ethylamine,  
N,N-bis(2-formyloxyethyl)-2-(2-formyloxyethoxycarbonyl)-  
ethylamine,  
35 N,N-bis(2-methoxyethyl)-2-(methoxycarbonyl)ethylamine,  
N-(2-hydroxyethyl)-bis[2-(methoxycarbonyl)ethyl]amine,  
N-(2-acetoxyethyl)-bis[2-(methoxycarbonyl)ethyl]amine,

N-(2-hydroxyethyl)-bis[2-(ethoxycarbonyl)ethyl]amine,  
N-(2-acetoxyethyl)-bis[2-(ethoxycarbonyl)ethyl]amine,  
N-(3-hydroxy-1-propyl)-bis[2-(methoxycarbonyl)ethyl]amine,  
N-(3-acetoxy-1-propyl)-bis[2-(methoxycarbonyl)ethyl]amine,  
5 N-(2-methoxyethyl)-bis[2-(methoxycarbonyl)ethyl]amine,  
N-butyl-bis[2-(methoxycarbonyl)ethyl]amine,  
N-butyl-bis[2-(2-methoxyethoxycarbonyl)ethyl]amine,  
N-methyl-bis(2-acetoxyethyl)amine,  
N-ethyl-bis(2-acetoxyethyl)amine,  
10 N-methyl-bis(2-pivaloyloxyethyl)amine,  
N-ethyl-bis[2-(methoxycarbonyloxy)ethyl]amine,  
N-ethyl-bis[2-(tert-butoxycarbonyloxy)ethyl]amine,  
tris(methoxycarbonylmethyl)amine,  
tris(ethoxycarbonylmethyl)amine,  
15 N-butyl-bis(methoxycarbonylmethyl)amine,  
N-hexyl-bis(methoxycarbonylmethyl)amine, and  
 $\beta$ -(diethylamino)- $\delta$ -valerolactone.

Also useful are one or more of cyclic structure-bearing basic compounds having the following general formula (B)-2.



(B)-2

Herein X is as defined above, and R<sup>307</sup> is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain one or more carbonyl, ether, ester or sulfide groups.

25 Illustrative examples of the cyclic structure-bearing basic compounds having formula (B)-2 include

1-[2-(methoxymethoxy)ethyl]pyrrolidine,

1-[2-(methoxymethoxy)ethyl]piperidine,

4-[2-(methoxymethoxy)ethyl]morpholine,

30 1-[2-[(2-methoxyethoxy)methoxy]ethyl]pyrrolidine,

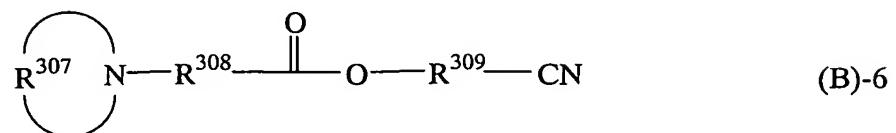
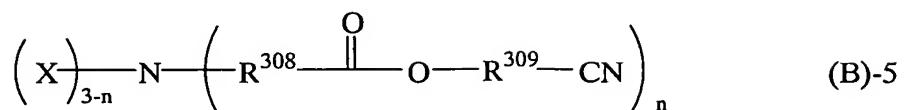
1-[2-[(2-methoxyethoxy)methoxy]ethyl]piperidine,

4-[2-[(2-methoxyethoxy)methoxy]ethyl]morpholine,

2-(1-pyrrolidinyl)ethyl acetate, 2-piperidinoethyl acetate,

2-morpholinoethyl acetate, 2-(1-pyrrolidinyl)ethyl formate,  
2-piperidinoethyl propionate,  
2-morpholinoethyl acetoxyacetate,  
2-(1-pyrrolidinyl)ethyl methoxyacetate,  
5 4-[2-(methoxycarbonyloxy)ethyl]morpholine,  
1-[2-(t-butoxycarbonyloxy)ethyl]piperidine,  
4-[2-(2-methoxyethoxycarbonyloxy)ethyl]morpholine,  
methyl 3-(1-pyrrolidinyl)propionate,  
methyl 3-piperidinopropionate, methyl 3-morpholinopropionate,  
10 methyl 3-(thiomorpholino)propionate,  
methyl 2-methyl-3-(1-pyrrolidinyl)propionate,  
ethyl 3-morpholinopropionate,  
methoxycarbonylmethyl 3-piperidinopropionate,  
2-hydroxyethyl 3-(1-pyrrolidinyl)propionate,  
15 2-acetoxyethyl 3-morpholinopropionate,  
2-oxotetrahydrofuran-3-yl 3-(1-pyrrolidinyl)propionate,  
tetrahydrofurfuryl 3-morpholinopropionate,  
glycidyl 3-piperidinopropionate,  
2-methoxyethyl 3-morpholinopropionate,  
20 2-(2-methoxyethoxy)ethyl 3-(1-pyrrolidinyl)propionate,  
butyl 3-morpholinopropionate,  
cyclohexyl 3-piperidinopropionate,  
 $\alpha$ -(1-pyrrolidinyl)methyl- $\gamma$ -butyrolactone,  
 $\beta$ -piperidino- $\gamma$ -butyrolactone,  $\beta$ -morpholino- $\delta$ -valerolactone,  
25 methyl 1-pyrrolidinylacetate, methyl piperidinoacetate,  
methyl morpholinoacetate, methyl thiomorpholinoacetate,  
ethyl 1-pyrrolidinylacetate, and  
2-methoxyethyl morpholinoacetate.

Also, one or more of cyano-bearing basic compounds  
30 having the following general formulae (B)-3 to (B)-6 may be  
blended.



Herein, X, R<sup>307</sup> and n are as defined above, and R<sup>308</sup> and R<sup>309</sup> are each independently a straight or branched alkylene group of 1 to 4 carbon atoms.

- 5      Illustrative examples of the cyano-bearing basic compounds having formulae (B)-3 to (B)-6 include  
 3-(diethylamino)propiononitrile,  
 N,N-bis(2-hydroxyethyl)-3-aminopropiononitrile,  
 N,N-bis(2-acetoxyethyl)-3-aminopropiononitrile,  
 10     N,N-bis(2-formyloxyethyl)-3-aminopropiononitrile,  
 N,N-bis(2-methoxyethyl)-3-aminopropiononitrile,  
 N,N-bis[2-(methoxymethoxy)ethyl]-3-aminopropiononitrile,  
 methyl N-(2-cyanoethyl)-N-(2-methoxyethyl)-3-aminopropionate,  
 methyl N-(2-cyanoethyl)-N-(2-hydroxyethyl)-3-aminopropionate,  
 15     methyl N-(2-acetoxyethyl)-N-(2-cyanoethyl)-3-aminopropionate,  
 N-(2-cyanoethyl)-N-ethyl-3-aminopropiononitrile,  
 N-(2-cyanoethyl)-N-(2-hydroxyethyl)-3-aminopropiononitrile,  
 N-(2-acetoxyethyl)-N-(2-cyanoethyl)-3-aminopropiononitrile,  
 N-(2-cyanoethyl)-N-(2-formyloxyethyl)-3-aminopropiononitrile,  
 20     N-(2-cyanoethyl)-N-(2-methoxyethyl)-3-aminopropiononitrile,

N-(2-cyanoethyl)-N-[2-(methoxymethoxy)ethyl]-3-aminopropiono-nitrile,  
N-(2-cyanoethyl)-N-(3-hydroxy-1-propyl)-3-aminopropiono-nitrile,  
5 N-(3-acetoxy-1-propyl)-N-(2-cyanoethyl)-3-aminopropiono-nitrile,  
N-(2-cyanoethyl)-N-(3-formyloxy-1-propyl)-3-aminopropiono-nitrile,  
N-(2-cyanoethyl)-N-tetrahydrofurfuryl-3-aminopropiononitrile,  
10 N,N-bis(2-cyanoethyl)-3-aminopropiononitrile,  
diethylaminoacetonitrile,  
N,N-bis(2-hydroxyethyl)aminoacetonitrile,  
N,N-bis(2-acetoxyethyl)aminoacetonitrile,  
N,N-bis(2-formyloxyethyl)aminoacetonitrile,  
15 N,N-bis(2-methoxyethyl)aminoacetonitrile,  
N,N-bis[2-(methoxymethoxy)ethyl]aminoacetonitrile,  
methyl N-cyanomethyl-N-(2-methoxyethyl)-3-aminopropionate,  
methyl N-cyanomethyl-N-(2-hydroxyethyl)-3-aminopropionate,  
methyl N-(2-acetoxyethyl)-N-cyanomethyl-3-aminopropionate,  
20 N-cyanomethyl-N-(2-hydroxyethyl)aminoacetonitrile,  
N-(2-acetoxyethyl)-N-(cyanomethyl)aminoacetonitrile,  
N-cyanomethyl-N-(2-formyloxyethyl)aminoacetonitrile,  
N-cyanomethyl-N-(2-methoxyethyl)aminoacetonitrile,  
N-cyanomethyl-N-[2-(methoxymethoxy)ethyl]aminoacetonitrile,  
25 N-cyanomethyl-N-(3-hydroxy-1-propyl)aminoacetonitrile,  
N-(3-acetoxy-1-propyl)-N-(cyanomethyl)aminoacetonitrile,  
N-cyanomethyl-N-(3-formyloxy-1-propyl)aminoacetonitrile,  
N,N-bis(cyanomethyl)aminoacetonitrile,  
1-pyrrolidinepropiononitrile, 1-piperidinepropiononitrile,  
30 4-morpholinepropiononitrile, 1-pyrrolidineacetonitrile,  
1-piperidineacetonitrile, 4-morpholineacetonitrile,  
cyanomethyl 3-diethylaminopropionate,  
cyanomethyl N,N-bis(2-hydroxyethyl)-3-aminopropionate,  
cyanomethyl N,N-bis(2-acetoxyethyl)-3-aminopropionate,  
35 cyanomethyl N,N-bis(2-formyloxyethyl)-3-aminopropionate,  
cyanomethyl N,N-bis(2-methoxyethyl)-3-aminopropionate,

cyanomethyl N,N-bis[2-(methoxymethoxy)ethyl]-3-aminopropionate,  
2-cyanoethyl 3-diethylaminopropionate,  
2-cyanoethyl N,N-bis(2-hydroxyethyl)-3-aminopropionate,  
5 2-cyanoethyl N,N-bis(2-acetoxyethyl)-3-aminopropionate,  
2-cyanoethyl N,N-bis(2-formyloxyethyl)-3-aminopropionate,  
2-cyanoethyl N,N-bis(2-methoxyethyl)-3-aminopropionate,  
2-cyanoethyl N,N-bis[2-(methoxymethoxy)ethyl]-3-aminopropionate,  
10 cyanomethyl 1-pyrrolidinopropionate,  
cyanomethyl 1-piperidinepropionate,  
cyanomethyl 4-morpholinepropionate,  
2-cyanoethyl 1-pyrrolidinopropionate,  
2-cyanoethyl 1-piperidinepropionate, and  
15 2-cyanoethyl 4-morpholinepropionate.

The conventional basic compounds may be used alone or in admixture of two or more. The conventional basic compound is preferably formulated in an amount of 0 to 2 parts, and especially 0 to 1 part by weight, per 100 parts by weight of  
20 the base resin.

In addition to the above components, the inventive resist composition may optionally include additives such as surfactants and acidic compounds.

Patterning with the inventive resist composition may  
25 be carried out by a conventional process. Such a process typically includes the steps of:

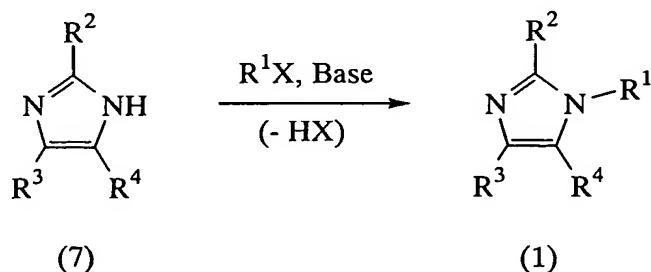
- (1) applying the above-described chemical amplification resist composition onto a substrate;
- (2) heat treating the applied resist, then exposing the  
30 heat-treated resist through a photomask to high-energy radiation having a wavelength of at most 300 nm, preferably at most 250 nm, or an electron beam; and
- (3) heat treating the exposed resist, then developing the resist with a liquid developer.

35 It is desirable for the basic compound of the invention to be included in an amount of 0.001 to 2 parts by

weight, and especially 0.01 to 1 part by weight, per 100 parts by weight of the overall base resin. The use of less than 0.001 part may have no perceivable effect, whereas the use of more than 2 parts may lower the sensitivity of the resist.

Preferably, the basic compound of the invention having an imidazole skeleton and a polar functional group, represented by formulae (1) to (6), is prepared by a method which is selected optimal for the structure of the compound. Specific, non-limiting, examples are a method using N-alkylation reaction of imidazole compounds, and a method using O-acylation or O-alkylation reaction of imidazole compounds having a hydroxyalkyl substituent group on N. The preparation methods are described in detail.

15 The first method is a preparation method using  
N-alkylation reaction of imidazole compounds. Basically, the  
method is applicable to the synthesis of all basic compounds  
having formulae (1) to (6).



20 In the above formulae, R<sup>1</sup> is a straight, branched or cyclic alkyl group of 2 to 20 carbon atoms bearing at least one polar functional group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms. X is an eliminatable group such as a halogen atom, p-toluenesulfonyloxy, methanesulfonyloxy, trifluoromethanesulfonyloxy or hydroxyl group.

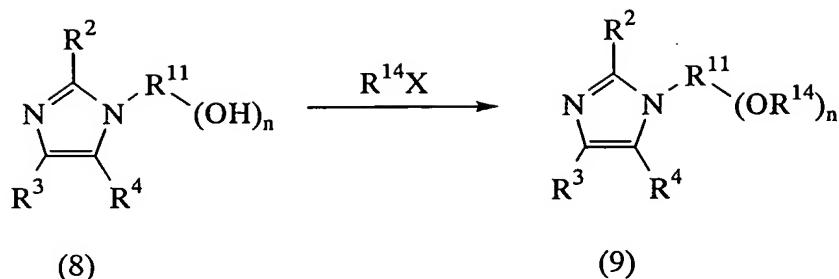
In the above reaction, it is desirable to use the alkylating agent  $R^1X$  in an amount of 0.3 to 10 moles, and especially 0.5 to 2 moles, per mole of the imidazole compound (7). The reaction may be carried out in a solvent or in the absence of a solvent. Solvents that may be selected in accordance with the reaction conditions and used, either singly or as mixtures thereof, include alcohols such as methanol, ethanol, isopropyl alcohol, t-butyl alcohol and ethylene glycol; hydrocarbons such as hexane, heptane, benzene, toluene and xylene; ethers such as diethyl ether, dibutyl ether, tetrahydrofuran, 1,4-dioxane and diglyme; chlorinated solvents such as methylene chloride, chloroform and 1,2-dichloroethylene; aprotic polar solvents such as N,N-dimethylformamide, N,N-dimethylacetamide, dimethylsulfoxide and N-methylpyrrolidone; carboxylic acids such as formic acid and acetic acid; esters such as ethyl acetate and butyl acetate; ketones such as acetone and 2-butanone; nitriles such as acetonitrile; amines such as pyridine and triethylamine; and water. The reaction temperature may be selected from a range of 0°C to the reflux temperature of the solvent, in accordance with the reaction rate. The base used in the invention may be selected in accordance with the reaction conditions from among amines such as pyridine, triethylamine, diisopropylethylamine, 4-dimethylaminopyridine and imidazole; metal alkoxides such as sodium methoxide, sodium ethoxide and potassium t-butoxide; carbonates such as sodium carbonate, potassium carbonate and cesium carbonate; hydroxides such as sodium hydroxide, potassium hydroxide and tetramethylammonium hydroxide; metal hydrides such as sodium hydride and potassium hydride; organometallic compounds such as butyllithium and ethyl magnesium bromide; and metal amides such as lithium diisopropylamide. Any one or mixture of these bases may be used. It is desirable to use the base in an amount of from 0.3 to 10 moles, and especially from 1 to 5 moles per mole of the imidazole compound (7). An iodide such as sodium iodide, lithium iodide or tetrabutylammonium iodide,

or a bromide such as sodium bromide, lithium bromide or tetrabutylammonium bromide, may be added as a catalyst to increase the reaction rate. When a catalyst is added, it is desirable for the amount of such addition to be from 0.001 to 5 2 moles, and especially from 0.005 to 0.5 mole, per mole of the imidazole compound (7). To maximize the final yield, it is desirable to monitor the progress of the reaction using gas chromatography (GC) or thin-layer chromatography (TLC) until the reaction is complete. Generally, the reaction time 10 is about 0.5 to 100 hours. The target imidazole compound (1) having a polar functional group is obtained by a conventional aqueous work-up from the reaction mixture. If necessary, compound (1) can be purified by an ordinary method such as distillation, chromatography or recrystallization.

15 Alternatively, it may be possible to omit the aqueous work-up, either by using filtration to collect the salt that has formed in the reaction and subjecting the collected salt to purification, or by furnishing the reaction mixture directly to purification.

20 Alternatively, the target imidazole compounds (1) having polar functional groups can be obtained, depending on the particular structure of the target compounds, by addition of imidazole compounds to cyclic ethers such as ethylene oxide, propylene oxide, glycidol and oxetane,  $\alpha,\beta$ -unsaturated 25 carbonyl compounds such as acrylic acid esters and acrylonitrile, and carbonates such as ethylene carbonate and propylene carbonate.

The second method is a preparation method using O-acylation or O-alkylation reaction of imidazole compounds 30 having a hydroxyalkyl substituent group on N. This method is effective especially for the preparation of basic compounds having formulae (2), (3) and (5).



In the formulae, R<sup>2</sup>, R<sup>3</sup> and R<sup>4</sup> are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms,  
5 or an aralkyl group of 7 to 10 carbon atoms; R<sup>11</sup> is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 1 to 10 carbon atoms having a polar functional group; R<sup>14</sup> is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain at least one group selected  
10 from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; X is an eliminatable group such as a halogen atom, alkylsulfonyloxy, arylsulfonyloxy, hydroxyl, acyloxy, phenoxy, or alkoxy group, and n is equal to 1, 2, 3, 4 or 5.

15 It is noted that the compounds (9) wherein n=1 and  $R^{14}X$   
= alkylating agent correspond to compounds of formula (2),  
the compounds (9) wherein n=1 and  $R^{14}X$  = acylating agent  
correspond to compounds of formula (3), and the compounds (9)  
wherein n = 2, 3, 4 or 5 correspond to compounds of formula  
20 (5).

In the above reaction, the alkylating or acylating agent  $R^{14}X$  acts on the N-(hydroxyalkyl)imidazole compound (8), which has been prepared by the first method or the like, yielding the target polar functional group-bearing imidazole compound (9). When  $R^{14}$  is an alkyl group, examples of  $R^{14}X$  include, but are not limited to, methyl iodide, butyl bromide, dimethyl sulfate, ethyl iodide, diethyl sulfate, methoxymethyl chloride, (2-methoxyethoxy)methyl chloride, methyl chloroacetate, and chloroacetone. When  $R^{14}$  is an acyl group, examples of  $R^{14}X$  include, but are not limited to, formic acid, acetic formic anhydride, acetic anhydride,

acetic chloride, propionic anhydride, propionic chloride,  
butyric chloride, isobutyric chloride, valeric chloride,  
pivalic chloride, methoxyacetic chloride, acetoxyacetic  
chloride, di-t-butyl pyrocarboxylate, phenyl acetate,  
5 p-nitrophenyl acetate, and 2,4,6-trichlorophenyl acetate. An  
appropriate amount of R<sup>14</sup>X used per mole of the  
N-(hydroxyalkyl)imidazole compound (8) is from 0.5 to 5.0  
moles, especially from 1.0 to 2.5 moles in the event n=1, and  
from 1.0 to 10 moles, especially from 2.0 to 5.0 moles in the  
10 event n=2. In sequence, the amount is accordingly increased  
as the value of n increases.

The reaction may be carried out in a solvent or in the  
absence of a solvent. Solvents that may be selected in  
accordance with the reaction conditions and used, either  
15 singly or as mixtures thereof, include hydrocarbons such as  
hexane, heptane, benzene, toluene and xylene; ethers such as  
diethyl ether, dibutyl ether, tetrahydrofuran, 1,4-dioxane  
and diglyme; chlorinated solvents such as methylene chloride,  
chloroform and 1,2-dichloroethylene; aprotic polar solvents  
20 such as N,N-dimethylformamide, N,N-dimethylacetamide,  
dimethylsulfoxide and N-methylpyrrolidone; carboxylic acids  
such as formic acid and acetic acid; esters such as ethyl  
acetate and butyl acetate; ketones such as acetone and  
25 2-butanone; nitriles such as acetonitrile; amines such as  
pyridine and triethylamine; alcohols such as methanol,  
ethanol, 2-propanol and t-butyl alcohol; and water.

In order to promote the reaction, a basic compound may  
be added. Examples include, but are not limited to, salts of  
alkali or alkaline earth metals such as sodium hydroxide,  
30 potassium hydroxide, potassium carbonate, sodium carbonate,  
sodium hydrogen carbonate, sodium hydride, calcium hydride,  
potassium t-butoxide, and lithium t-butoxide; organometal  
compounds such as n-butyllithium, lithium diisopropylamide,  
lithium hexamethyldisilazide, bromomagnesium  
35 diisopropylamide; and organic amines such as pyridine,  
triethylamine, diisopropylethylamine, N,N-dimethylaniline,  
and 4-dimethylaminopyridine. The basic compound may be used

alone or in admixture. An appropriate amount of the basic compound used is from 0.8 to 10 moles, especially from 0.9 to 3.0 moles per mole of  $R^{14}X$ . The reaction temperature may be selected from a range of -70°C to the reflux temperature of the solvent, preferably 0°C to 50°C. In the event  $R^{14}$  = acyl and X = alkoxy,  $R^{14}X$  is a carboxylic acid ester, and the instant reaction is a transesterification reaction. In this event, the above-mentioned basic compound is used as a catalyst in an amount of 0.001 to 5.0 moles, especially 0.005 to 0.5 mole per mole of  $R^{14}X$ , and reaction is preferably carried out while distilling off the alcohol (X-H) formed during the reaction. To maximize the final yield, it is desirable to monitor the progress of the reaction using gas chromatography (GC) or thin-layer chromatography (TLC) until the reaction is complete. Generally, the reaction time is about 0.2 to 20 hours. The target polar functional group-bearing imidazole compound (1) is obtained by a conventional aqueous work-up from the reaction mixture. If necessary, compound (1) can be purified by an ordinary method such as distillation, chromatography or recrystallization. Alternatively, it may be possible to omit the aqueous work-up, either by using filtration to collect the salt that has formed in the reaction and subjecting the collected salt to purification, or by furnishing the reaction mixture directly to purification.

Resist compositions prepared using the basic compounds having an imidazole skeleton and a polar functional group according to the invention are endowed with an excellent resolution and an excellent focus margin, and are thus useful in microfabrication using electron beams or deep-UV light. The addition of such compounds imparts significant effects in KrF resists, ArF resists, F<sub>2</sub> resists and EB resists. Such resists are highly suitable as micropatterning materials in the manufacture of VLSI chips.

## EXAMPLES

Examples and comparative examples are given below by way of illustration, and not by way of limitation.

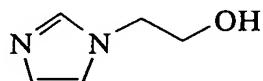
Basic compounds of the invention were synthesized by 5 the procedure below.

### Synthesis Example 1

#### Synthesis of 2-(1H-imidazol-1-yl)ethanol (Amine 1)

A mixture of 68.0 g of imidazole, 48.5 g of ethylene oxide, and 200 g of N,N-dimethylacetamide was heated and 10 stirred in an autoclave at 100°C for 16 hours. The solvent was distilled off in vacuo, after which the reaction mixture was purified by column chromatography, obtaining 89.7 g of 2-(1H-imidazol-1-yl)ethanol (yield 80%).

15  $^1\text{H-NMR}$  (600 MHz in  $\text{CDCl}_3$ ):  $\delta = 3.86$  (2H, t,  $J=5.4$  Hz), 4.06 (2H, t,  $J=5.4$  Hz), 4.41 (1H, br.), 6.97 (1H, m), 6.99 (1H, m), 7.57 (1H, m)

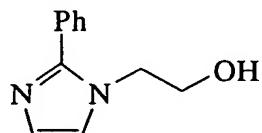


Amine 1

### Synthesis Example 2

#### Synthesis of 2-(2-phenyl-1H-imidazol-1-yl)ethanol (Amine 7)

The procedure of Synthesis Example 1 was repeated aside from using an equimolar amount of 2-phenylimidazole instead of imidazole. There was synthesized 25 2-(2-phenyl-1H-imidazol-1-yl)ethanol (yield 83%).



Amine 7

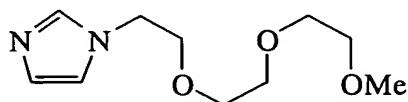
Synthesis Example 3

Synthesis of 1-[2-[2-(2-methoxyethoxy)ethoxy]ethyl]-1H-imidazole (Amine 22)

In a nitrogen atmosphere, a mixture of 68.0 g of imidazole, 318 g of 2-[2-(2-methoxyethoxy)ethoxy]ethyl p-toluenesulfonate, 276 g of potassium carbonate, and 1,000 g of N,N-dimethylformamide was heated and stirred at 100°C for 16 hours. To the reaction solution was added ethyl acetate. The precipitate was filtered off, after which the solvent was distilled off in vacuo. The residue was purified by distillation in vacuo, obtaining 163 g of 1-[2-[2-(2-methoxyethoxy)ethoxy]ethyl]-1H-imidazole (boiling point 121°C/16 Pa, yield 76%).

IR (thin film):  $\nu$  = 3108, 2875, 1508, 1452, 1353, 1286, 1232, 1199, 1106, 1029, 906, 850, 823, 744, 667, 626  $\text{cm}^{-1}$

$^1\text{H-NMR}$  (600 MHz in  $\text{CDCl}_3$ ):  $\delta$  = 3.34 (3H, s), 3.50 (2H, t,  $J=4.5$  Hz), 3.55-3.60 (6H, m), 3.71 (2H, t,  $J=5.1$  Hz), 4.07 (2H, t,  $J=5.1$  Hz), 6.96 (1H, m), 7.00 (1H, m), 7.50 (1H, m)



Amine 22

20

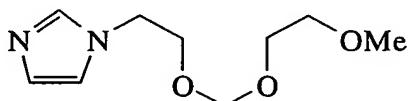
Synthesis Example 4

Synthesis of 1-[2-[(2-methoxyethoxy)methoxy]ethyl]-1H-imidazole (Amine 24)

The procedure of Synthesis Example 3 was repeated aside from using an equimolar amount of 1-bromo-2-[(2-methoxyethoxy)methoxy]ethane instead of 2-[2-(2-methoxyethoxy)ethoxy]ethyl p-toluenesulfonate. There was synthesized 1-[2-[(2-methoxyethoxy)methoxy]ethyl]-1H-imidazole (boiling point 110°C/15 Pa, yield 74%).

IR (thin film):  $\nu = 3108, 2931, 2881, 2819, 1508, 1450, 1363, 1286, 1232, 1199, 1170, 1118, 1095, 1047, 906, 846, 742, 667, 624 \text{ cm}^{-1}$

<sup>1</sup>H-NMR (600 MHz in CDCl<sub>3</sub>): δ = 3.33 (3H, s), 3.41 (2H, m),  
 3.12 (2H, m), 3.77 (2H, t, J=5.1 Hz), 4.10 (2H, t,  
 J=5.1 Hz), 6.94 (1H, m), 7.01 (1H, m), 7.49 (1H, m)



## Amine 24

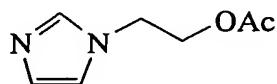
### Synthesis Example 5

#### 10 Synthesis of 2-(1H-imidazol-1-yl)ethyl acetate (Amine 37)

In a nitrogen atmosphere, a mixture of 112 g of 2-(1H-imidazol-1-yl)ethanol, synthesized in Synthesis Example 1, and 122 g of acetic anhydride was stirred at room temperature for 16 hours. The reaction mixture was subjected to conventional aqueous work-up and then purified by vacuum distillation, obtaining 131 g of 2-(1H-imidazol-1-yl)ethyl acetate (boiling point 102° C/27 Pa, yield 85%).

IR (thin film):  $\nu$  = 3110, 2958, 1741, 1508, 1442, 1380, 1288,  
 1232, 1108, 1078, 1051, 906, 817, 744, 667  $\text{cm}^{-1}$

20  $^1\text{H-NMR}$  (600 MHz in  $\text{CDCl}_3$ ):  $\delta$  = 2.01 (3H, s), 4.16 (2H, t,  
 J=5.3 Hz), 4.27 (2H, t, J=5.3 Hz), 6.91 (1H, m), 7.02  
 (1H, m), 7.47 (1H, m)



## Amine 37

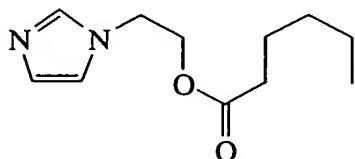
Synthesis Example 6

Synthesis of 2-(1H-imidazol-1-yl)ethyl caproate (Amine 55)

In a nitrogen atmosphere, 148 g of caproyl chloride was added dropwise to a mixture of 112 g of 2-(1H-imidazol-1-yl)ethanol, synthesized in Synthesis Example 1, 121 g of triethylamine and 1,000 g of methylene chloride at 0°C. Then the reaction mixture was heated at 20°C and stirred for 5 hours. The reaction mixture was subjected to conventional aqueous work-up and then purified by vacuum distillation, obtaining 189 g of 2-(1H-imidazol-1-yl)ethyl caproate (boiling point 127°C/20 Pa, yield 90%).

IR (thin film):  $\nu$  = 2956, 2933, 2871, 1737, 1506, 1457, 1378, 1286, 1232, 1168, 1108, 1076, 1039, 906, 817, 736, 665, 624  $\text{cm}^{-1}$

<sup>1</sup>H-NMR (600 MHz in CDCl<sub>3</sub>):  $\delta$  = 0.86 (3H, t, J=7.2 Hz), 1.20-1.32 (4H, m), 1.57 (2H, tt, J=7.6, 7.5 Hz), 2.27 (2H, t, J=7.6 Hz), 4.17 (2H, t, J=5.4 Hz), 4.29 (2H, t, J=5.4 Hz), 6.92 (1H, m), 7.03 (1H, m), 7.47 (1H, m)



Amine 55

20

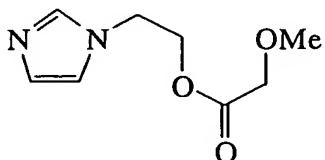
Synthesis Example 7

Synthesis of 2-(1H-imidazol-1-yl)ethyl methoxyacetate (Amine 56)

In a nitrogen atmosphere, a mixture of 112 g of 2-(1H-imidazol-1-yl)ethanol, synthesized in Synthesis Example 1, 156 g of methyl methoxyacetate, 3.0 g of sodium methoxide, and 200 g of toluene was heated under reflux for 20 hours while distilling off the methanol formed during the reaction. The solvent was distilled off in vacuo. Purification by vacuum distillation gave 166 g of 2-(1H-imidazol-1-yl)ethyl methoxyacetate (boiling point 126°C/27 Pa, yield 90%).

IR (thin film):  $\nu$  = 2991, 2942, 2827, 1754, 1508, 1450, 1386,  
 1361, 1288, 1232, 1189, 1128, 1079, 1039, 937, 906,  
 823, 746, 665, 624  $\text{cm}^{-1}$

<sup>1</sup>H-NMR (600 MHz in CDCl<sub>3</sub>):  $\delta$  = 3.38 (3H, s), 4.00 (2H, s),  
 4.20 (2H, t, J=5.3 Hz), 4.27 (2H, t, J=5.3 Hz), 6.92  
 (1H, m), 7.02 (1H, m), 7.45 (1H, m)

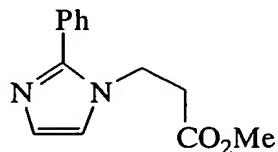


Amine 56

Synthesis Example 8

10 Synthesis of methyl 3-(2-phenyl-1H-imidazol-1-yl)propionate  
 (Amine 66)

A mixture of 144 g of 2-phenylimidazole, 103 g of methyl acrylate and 500 g of methanol was heated and stirred at 60° C for 20 hours. The solvent was distilled off in vacuo. Purification by column chromatography gave 193 g of methyl 3-(2-phenyl-1H-imidazol-1-yl)propionate (yield 84%).



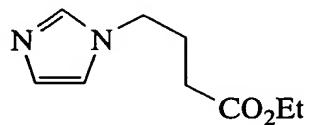
Amine 66

Synthesis Example 9

20 Synthesis of ethyl 4-(2-phenyl-1H-imidazol-1-yl)butyrate  
 (Amine 69)

The procedure of Synthesis Example 3 was repeated aside from using an equimolar amount of ethyl 4-bromobutyrate instead of 2-[2-(2-methoxyethoxy)ethoxy]ethyl

p-toluenesulfonate. There was synthesized ethyl 4-(2-phenyl-1H-imidazol-1-yl)butyrate (yield 88%).

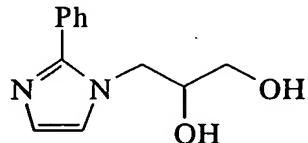


Amine 69

5    Synthesis Example 10

Synthesis of 3-(2-phenyl-1H-imidazol-1-yl)-1,2-propanediol (Amine 79)

The procedure of Synthesis Example 1 was repeated aside from using an equimolar amount of 2-phenylimidazole instead of imidazole and an equimolar amount of glycidol instead of ethylene oxide. There was synthesized 3-(2-phenyl-1H-imidazol-1-yl)-1,2-propanediol (yield 72%).

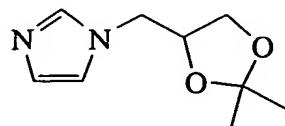


Amine 79

15    Synthesis Example 11

Synthesis of 1-[(2,2-dimethyl-1,3-dioxolan-4-yl)methyl]-1H-imidazole (Amine 83)

The procedure of Synthesis Example 3 was repeated aside from using an equimolar amount of 4-bromomethyl-2,2-dimethyl-1,3-dioxolane instead of 2-[2-(2-methoxyethoxy)ethoxy]ethyl p-toluenesulfonate. There was synthesized 1-[(2,2-dimethyl-1,3-dioxolan-4-yl)methyl]-1H-imidazole (yield 88%).



Amine 83

Synthesis Example 12

Synthesis of 1-[(1,3-dioxolan-2-yl)methyl]-1H-imidazole  
(Amine 89)

The procedure of Synthesis Example 3 was repeated  
5 aside from using an equimolar amount of 2-bromomethyl-1,3-dioxolane instead of 2-[2-(2-methoxyethoxy)ethoxy]ethyl p-toluenesulfonate. There was synthesized 1-[(1,3-dioxolan-2-yl)methyl]-1H-imidazole (yield 78%).



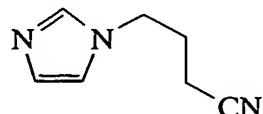
Amine 89

10

Synthesis Example 13

Synthesis of 4-(1H-imidazol-1-yl)butyronitrile (Amine 94)

The procedure of Synthesis Example 3 was repeated  
aside from using an equimolar amount of 4-bromobutyronitrile  
15 instead of 2-[2-(2-methoxyethoxy)ethoxy]ethyl p-toluenesulfonate. There was synthesized 4-(1H-imidazol-1-yl)butyronitrile (yield 83%).



Amine 94

20 Synthesis Example 14

Synthesis of 1-tetrahydrofurfuryl-1H-imidazole (Amine 99)

The procedure of Synthesis Example 3 was repeated  
aside from using an equimolar amount of tetrahydrofurfuryl bromide instead of 2-[2-(2-methoxyethoxy)ethoxy]ethyl p-toluenesulfonate. There was synthesized 1-tetrahydrofurfuryl-1H-imidazole (yield 70%).

IR (thin film):  $\nu$  = 3106, 2973, 2948, 2871, 1506, 1438, 1378,  
1324, 1284, 1232, 1106, 1072, 906, 819, 744, 665, 624  
 $\text{cm}^{-1}$

<sup>1</sup>H-NMR (600 MHz in CDCl<sub>3</sub>): δ = 1.47 (1H, m), 1.69 (1H, m), 5  
1.83 (1H, m), 1.95 (1H, m), 3.72 (1H, ddd, J=8.2, 7.6, 6.2 Hz), 3.79 (1H, ddd, J=8.2, 6.9, 6.5 Hz), 3.91 (1H, dd, J=14.1, 5.5 Hz), 4.05 (1H, dd, J=14.1, 3.8 Hz), 4.10 (1H, m), 6.96 (1H, m), 7.01 (1H, m), 7.48 (1H, m)

Resist Evaluation Examples:

In each example, a resist solution was prepared by dissolving a polymer, a photoacid generator, a base, a dissolution inhibitor and a crosslinking agent in a 70:30 by 10 weight solvent mixture of propylene glycol monomethyl ether acetate (PGMEA) and ethyl lactate (EL), then filtering the solution using a Teflon® filter having a pore size of 0.1 μm.

The resulting resist solution was spin-coated onto a silicon wafer substrate on which had been formed a 55 nm 15 thick film of DUV-30 (Nissan Chemical Industries, Ltd.) to hold the reflectance to KrF light (248 nm) to less than 1%, then baked at 100°C for 90 seconds on a hot plate, giving a resist film having a thickness of 550 nm.

The resist film was exposed using an excimer laser 20 stepper (NSR-S202A, manufactured by Nikon Corporation; NA = 0.6; σ = 0.75; 2/3 annular illumination) while varying the exposure dose and focus. Immediately after exposure, the resist was baked at 110°C for 90 seconds, then developed for 25 60 seconds with a 2.38% solution of tetramethylammonium hydroxide in water, giving a resist pattern.

The resulting resist patterns were evaluated as described below. The results are shown in the following tables.

Method of Evaluation:

An optimal exposure dose (E<sub>op</sub>) was the exposure which 30 provided a 1:1 resolution of 0.16 μm lines and spaces. A focus margin was determined at the optimal exposure dose (E<sub>op</sub>). The focus margin was defined as the absence of pattern film thickness loss and as having a size of not more 35 than 0.16 μm ± 10%.

**Table 1: Examples of Invention**

	Polymer (pbw)	Photoacid generator (pbw)	Base (pbw)	Dissolution inhibitor /Crosslinker (pbw)	Sensitivity (mJ/cm <sup>2</sup> )	Focus margin (μm)
Example	Polymer5 (100)	PAG3 (2)	Amine1 (0.1)	-	30	0.8
	Polymer5 (100)	PAG3 (2)	Amine7 (0.1)	-	35	0.8
	Polymer5 (100)	PAG3 (2)	Amine8 (0.1)	-	31	1.1
	Polymer5 (100)	PAG3 (2)	Amine10 (0.13)	-	30	0.8
	Polymer5 (100)	PAG3 (2)	Amine21 (0.13)	-	29	0.9
	Polymer5 (100)	PAG3 (2)	Amine22 (0.14)	-	28	1.1
	Polymer5 (100)	PAG3 (2)	Amine23 (0.1)	-	32	1.0
	Polymer5 (100)	PAG3 (2)	Amine24 (0.12)	-	39	1.0
	Polymer5 (100)	PAG3 (2)	Amine30 (0.11)	-	38	1.1
	Polymer5 (100)	PAG3 (2)	Amine31 (0.09)	-	39	1.0
	Polymer5 (100)	PAG3 (2)	Amine33 (0.12)	-	41	0.9
	Polymer5 (100)	PAG3 (2)	Amine34 (0.15)	-	42	1.1
	Polymer5 (100)	PAG3 (2)	Amine37 (0.12)	-	39	1.0
	Polymer5 (100)	PAG3 (2)	Amine38 (0.12)	-	41	1.2
	Polymer5 (100)	PAG3 (2)	Amine43 (0.14)	-	40	0.9
	Polymer5 (100)	PAG3 (2)	Amine44 (0.14)	-	41	1.1
	Polymer5 (100)	PAG3 (2)	Amine46 (0.1)	-	40	1.0
	Polymer5 (100)	PAG3 (2)	Amine49 (0.11)	-	39	1.0
	Polymer5 (100)	PAG3 (2)	Amine50 (0.12)	-	38	1.2
	Polymer5 (100)	PAG3 (2)	Amine51 (0.12)	-	41	1.0
	Polymer5 (100)	PAG3 (2)	Amine52 (0.16)	-	40	1.0
	Polymer5 (100)	PAG3 (2)	Amine54 (0.12)	-	37	1.1
	Polymer5 (100)	PAG3 (2)	Amine55 (0.14)	-	38	1.0
	Polymer5 (100)	PAG3 (2)	Amine56 (0.12)	-	37	0.9
	Polymer5 (100)	PAG3 (2)	Amine58 (0.15)	-	40	1.1
	Polymer5 (100)	PAG3 (2)	Amine59 (0.14)	-	39	1.0
	Polymer5 (100)	PAG3 (2)	Amine60 (0.15)	-	41	1.2

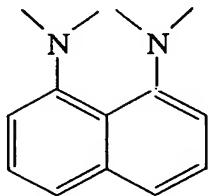
**Table 2: Examples of Invention**

	Polymer (pbw)	Photoacid generator (pbw)	Base (pbw)	Dissolution inhibitor /Crosslinker (pbw)	Sensitivity (mJ/cm <sup>2</sup> )	Focus margin (μm)
Example	Polymer5 (100)	PAG3 (2)	Amine61 (0.13)	-	37	0.9
	Polymer5 (100)	PAG3 (2)	Amine63 (0.14)	-	41	1.1
	Polymer5 (100)	PAG3 (2)	Amine66 (0.15)	-	41	1.0
	Polymer5 (100)	PAG3 (2)	Amine68 (0.14)	-	37	1.1
	Polymer5 (100)	PAG3 (2)	Amine69 (0.15)	-	35	0.8
	Polymer5 (100)	PAG3 (2)	Amine74 (0.11)	-	38	1.0
	Polymer5 (100)	PAG3 (2)	Amine79 (0.11)	-	34	0.8
	Polymer5 (100)	PAG3 (2)	Amine83 (0.12)	-	38	1.0
	Polymer5 (100)	PAG3 (2)	Amine86 (0.09)	-	35	0.8
	Polymer5 (100)	PAG3 (2)	Amine87 (0.1)	-	36	0.9
	Polymer5 (100)	PAG3 (2)	Amine89 (0.1)	-	40	1.0
	Polymer5 (100)	PAG3 (2)	Amine91 (0.11)	-	41	1.0
	Polymer5 (100)	PAG3 (2)	Amine94 (0.1)	-	38	0.9
	Polymer5 (100)	PAG3 (2)	Amine99 (0.13)	-	41	1.1
	Polymer1 (100)	PAG5 (2)	Amine37 (0.12)	-	45	0.9
	Polymer2 (100)	PAG5 (2)	Amine37 (0.12)	-	50	0.9
	Polymer3 (100)	PAG5 (2)	Amine37 (0.12)	-	48	1.1
	Polymer3 (100)	PAG4 (2)	Amine37 (0.12)	-	48	1.0
	Polymer4 (100)	PAG2 (2)	Amine37 (0.12)	Crosslinker (15)	33	0.8
	Polymer6 (100)	PAG1 (2)	Amine37 (0.12)	-	46	1.0
	Polymer7 (100)	PAG1 (2)	Amine37 (0.12)	-	48	1.0
	Polymer8 (100)	PAG1 (2)	Amine37 (0.12)	-	42	1.0
	Polymer9 (100)	PAG1 (2)	Amine37 (0.12)	-	40	0.8
	Polymer10 (100)	PAG1 (2)	Amine37 (0.12)	-	46	0.8
	Polymer11 (100)	PAG1 (2)	Amine37 (0.12)	-	44	0.8
	Polymer12 (100)	PAG4 (2)	Amine37 (0.12)	-	45	1.0
	Polymer13 (100)	PAG1 (2)	Amine37 (0.12)	-	47	0.9
	Polymer5 (100)	PAG2 (2)	Amine37 (0.12)	DRI (20)	31	1.0

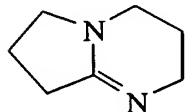
Table 3: Comparative Examples of Invention

	Polymer (pbw)	Photoacid generator (pbw)	Base (pbw)	Dissolution inhibitor /Crosslinker (pbw)	Sensitivity (mJ/cm <sup>2</sup> )	Focus margin (μm)
Comparative Example	Polymer5 (100)	PAG2 (2)	-	-	8	0.2
	Polymer5 (100)	PAG2 (2)	1,8-bis(dimethylamino)-naphthalene (0.2)	-	35	0.4
	Polymer5 (100)	PAG2 (2)	DBN (0.1)	-	34	0.4
	Polymer5 (100)	PAG2 (2)	DBU (0.1)	-	32	0.5
	Polymer1 (100)	PAG5 (2)	DBN (0.1)	-	52	0.2
	Polymer2 (100)	PAG5 (2)	DBN (0.1)	-	62	0.5
	Polymer3 (100)	PAG5 (2)	DBN (0.1)	-	51	0.3
	Polymer3 (100)	PAG4 (2)	DBN (0.1)	-	51	0.2
	Polymer4 (100)	PAG2 (2)	DBN (0.1)	Crosslinker1 (15)	33	0.3
	Polymer6 (100)	PAG1 (2)	DBN (0.1)	-	46	0.6
	Polymer7 (100)	PAG1 (2)	DBN (0.1)	-	48	0.6
	Polymer8 (100)	PAG1 (2)	DBN (0.1)	-	42	0.6
	Polymer9 (100)	PAG1 (2)	DBN (0.1)	-	45	0.4
	Polymer10 (100)	PAG1 (2)	DBN (0.1)	-	48	0.3
	Polymer11 (100)	PAG1 (2)	DBN (0.1)	-	42	0.4
	Polymer12 (100)	PAG4 (2)	DBN (0.1)	-	46	0.2
	Polymer13 (100)	PAG1 (2)	DBN (0.1)	-	45	0.3
	Polymer5 (100)	PAG2 (2)	DBN (0.1)	DRI1 (20)	29	0.3

**1,8-bis(dimethylamino)naphthalene**

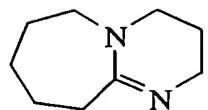


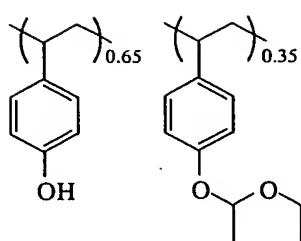
**DBN: 1,5-diazabicyclo[4.3.0]-5-nonene**



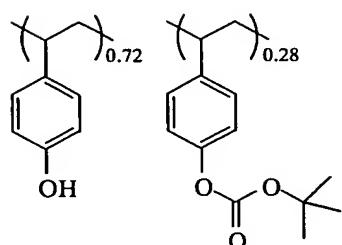
5

**DBU: 1,8-diazabicyclo[5.4.0]-7-undecene**

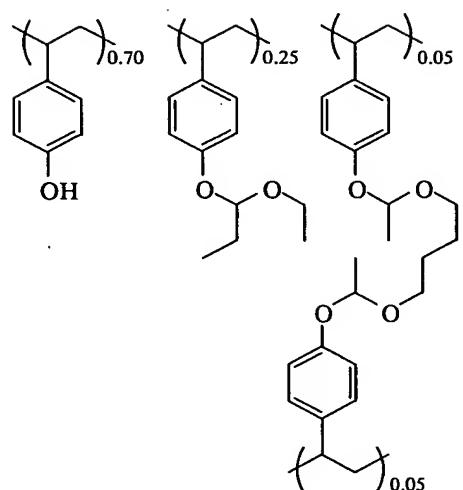




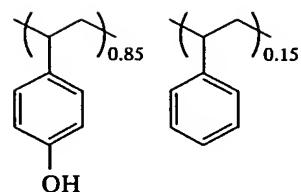
Polymer 1  
Mw 10,000  
Mw/Mn 1.10



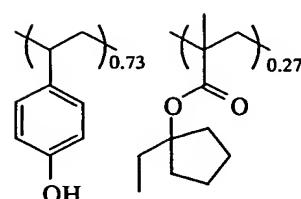
Polymer 2  
Mw 10,000  
Mw/Mn 1.10



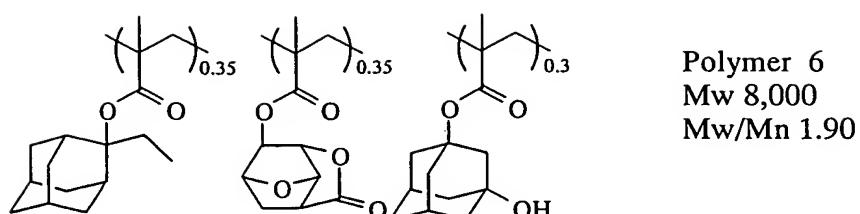
Polymer 3  
Mw 16,000  
Mw/Mn 1.60



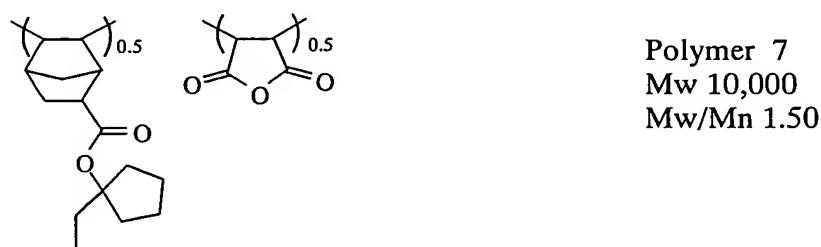
Polymer 4  
Mw 10,000  
Mw/Mn 1.10



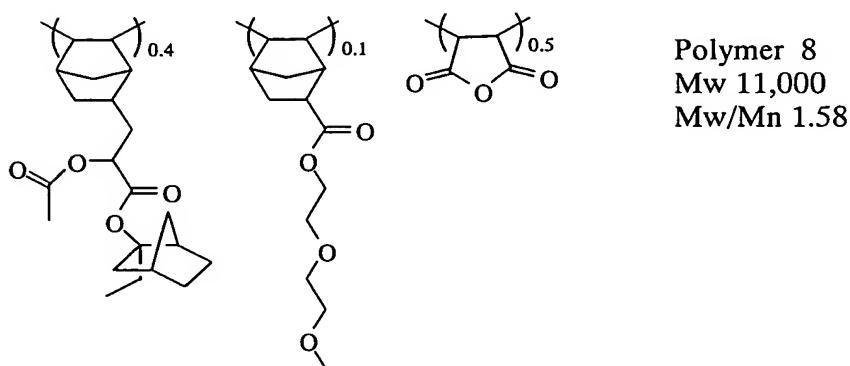
Polymer 5  
Mw 12,000  
Mw/Mn 1.60



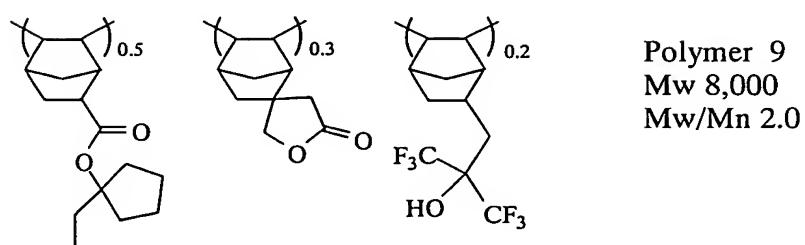
Polymer 6  
Mw 8,000  
Mw/Mn 1.90



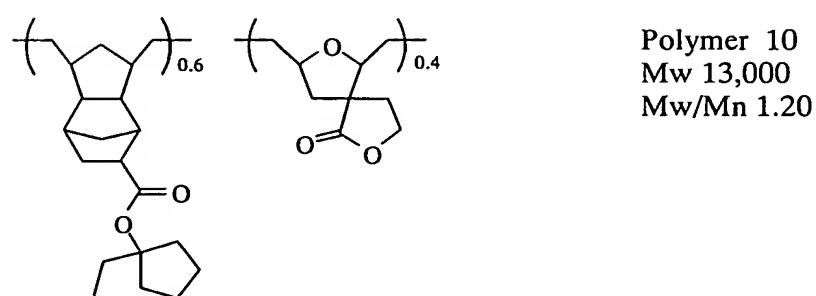
Polymer 7  
Mw 10,000  
Mw/Mn 1.50



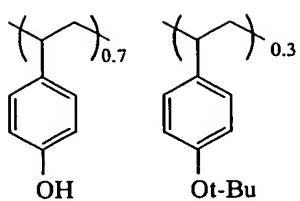
Polymer 8  
Mw 11,000  
Mw/Mn 1.58



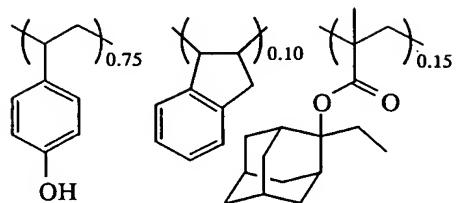
Polymer 9  
Mw 8,000  
Mw/Mn 2.0



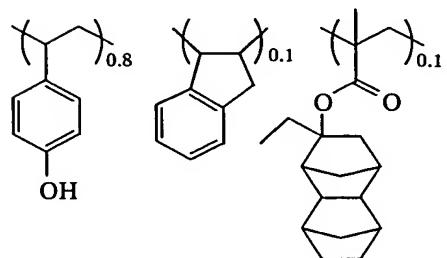
Polymer 10  
Mw 13,000  
Mw/Mn 1.20



Polymer 11  
Mw 8,000  
Mw/Mn 1.10



Polymer 12  
Mw 8,000  
Mw/Mn 1.80



Polymer 13  
Mw 8,000  
Mw/Mn 1.80

